

1 *Supplementary Information for*

2 **Atomically Engineering Interlayer Symmetry Operations of Two-** 3 **Dimensional Crystals**

4 Ziyi Han^{1,2,#}, Shengqiang Wu^{1,#}, Chun Huang^{3,#}, Fengyuan Xuan⁴, Xiaoxang Han¹, Yinfeng Long⁵, Qing
5 Zhang^{2,6,7}, Junxian Li¹, Yuan Meng¹, Lin Wang⁵, Jiahuan Zhou⁸, Wenping Hu^{2,6}, Jingsi Qiao³, Dechao
6 Geng^{2,6,7,*}, Xiaoxu Zhao^{1,*}

7 ¹School of Materials Science and Engineering, Peking University, Beijing 100871, China

8 ²Key Laboratory of Organic Integrated Circuits, Ministry of Education & Tianjin Key Laboratory of
9 Molecular Optoelectronic Sciences, Department of Chemistry, School of Science, Tianjin University, Tianjin
10 300072, China

11 ³MIT Key Laboratory for Low-Dimensional Quantum Structure and Devices & Advanced Research Institute
12 of Multidisciplinary Science, Beijing Institute of Technology, Beijing 100081, China

13 ⁴Suzhou Laboratory, Suzhou, 215123, China

14 ⁵School of Mechanical Engineering, Shanghai JiaoTong University, Shanghai 200240, China

15 ⁶Collaborative Innovation Center of Chemical Science and Engineering (Tianjin), Tianjin 300072, China

16 ⁷Beijing National Laboratory for Molecular Sciences, Beijing 100190, China

17 ⁸Wangxuan Institute of Computer Technology, Peking University, Beijing, China

18 Z. H., S. W. & C. H. contributed equally to this work

19

20 **Table of contents**

21 1. Supplementary Fig. 1-36

22 2. Supplementary Table 1-10

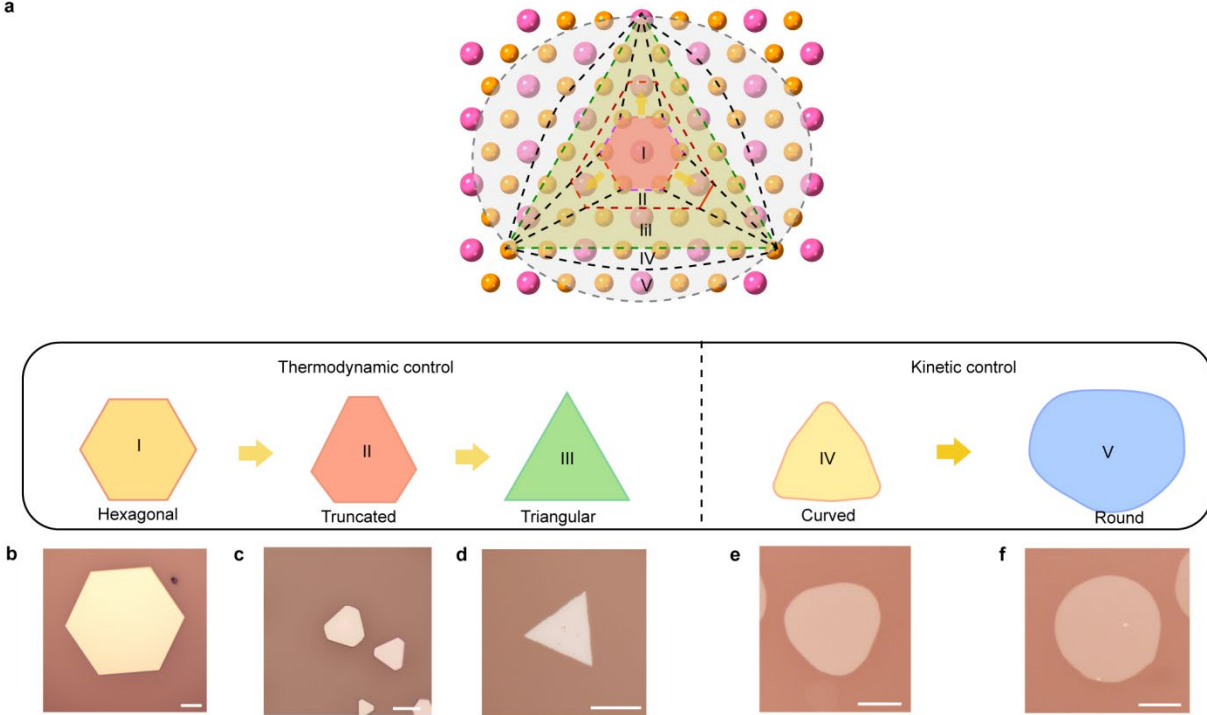
23 3. Supplementary Note 1-6

24 **Additional references**

25

26 1. Supplementary Fig. 1-36

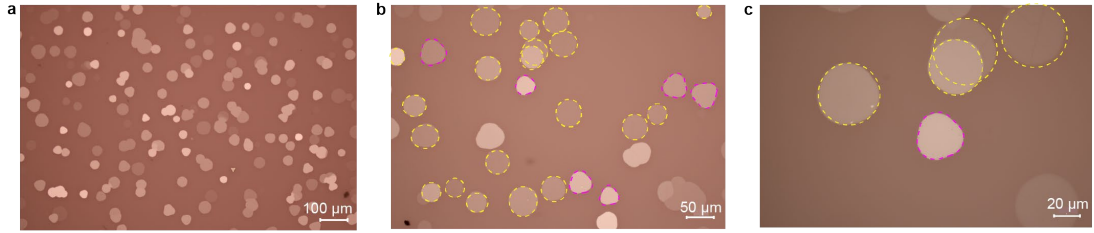
a



27

28 **Supplementary Fig. 1. Evolution of SnSe₂ shape as a function of growth conditions.** (a) Schematic
29 illustration of the morphology evolution of SnSe₂ flakes (marked by I, II, III, IV, and V, respectively). The
30 formation of hexagonal, truncated, and triangular SnSe₂ flakes is related to thermodynamic control,
31 whereas the formation of curved and round SnSe₂ flakes is correlated to kinetic control. Scale bars: 20 μm
32 in (b, e, f); 10 μm in (c, d).

33



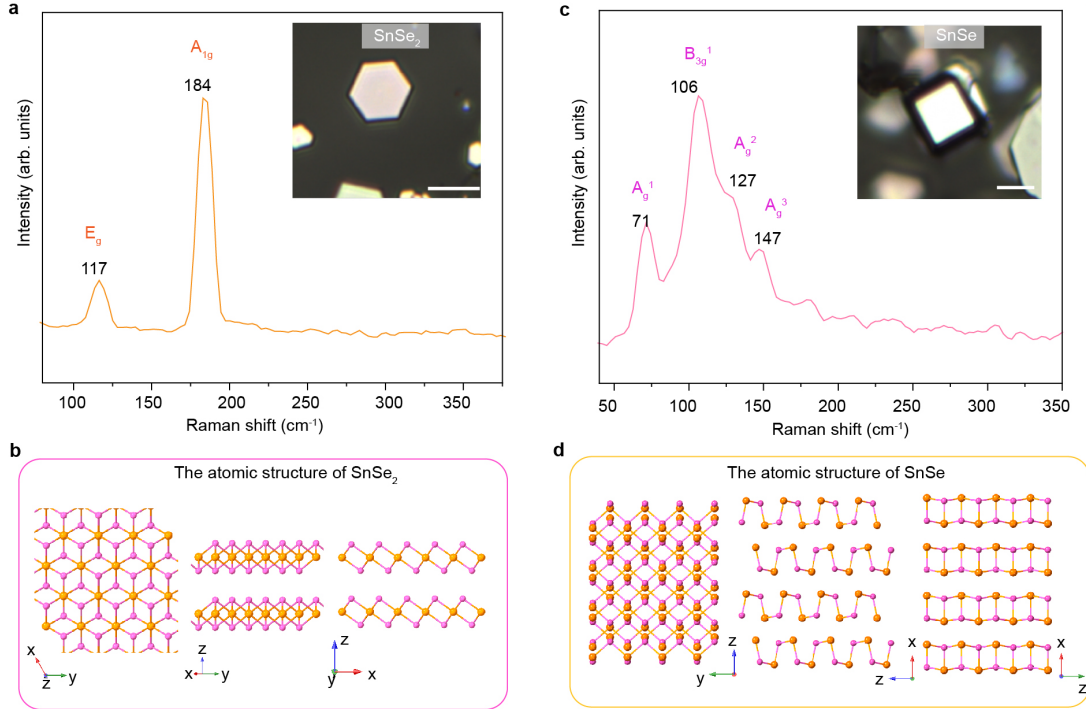
34

35 **Supplementary Fig. 2.** The optical image of AB'-stacked SnSe₂ crystals with irregular shapes marked by

36 pink and yellow dashed lines.

37

38

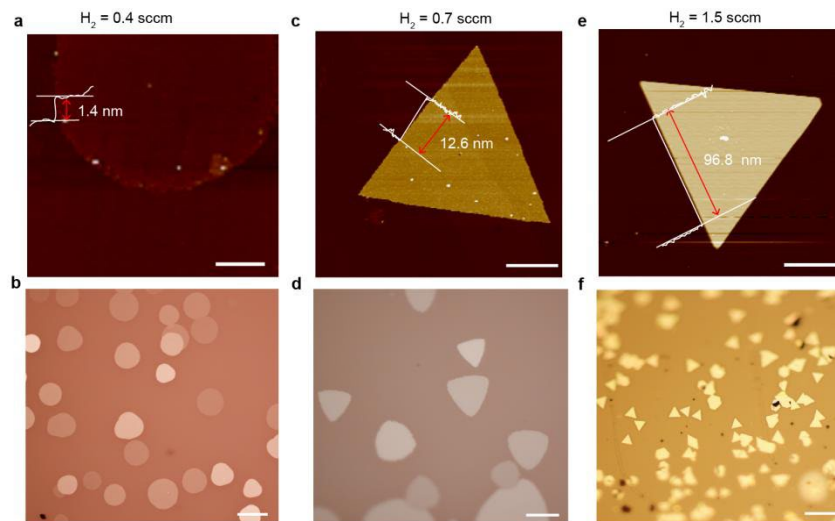


39

40 **Supplementary Fig. 3. The Raman spectra of SnSe₂ and SnSe.** The Raman spectra of SnSe₂ (a) and SnSe41 flake (b) and their atomic structure model, respectively. As for SnSe₂ crystals, 117 cm⁻¹ and 184 cm⁻¹42 corresponds to the E_{2g} and A_{1g} vibration modes, respectively. As for SnSe, 71 cm⁻¹, 106 cm⁻¹, 127 cm⁻¹ and43 147 cm⁻¹ correspond to the A_g¹, B_{3g}¹, A_g² and A_g³ vibration modes, respectively. Scale bar: 4 μm.

44

45

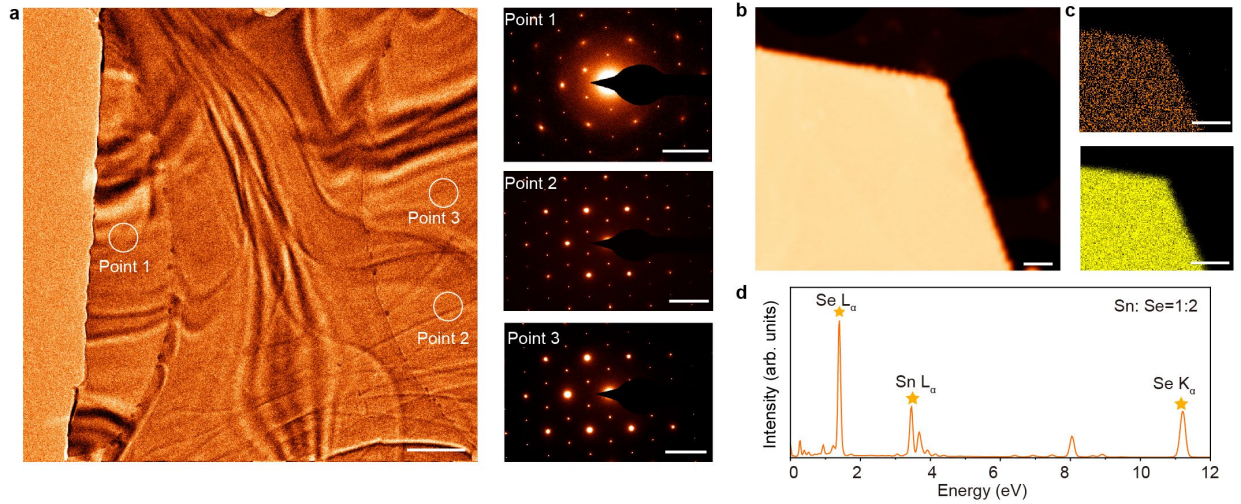


46

47 **Supplementary Fig. 4. Atomic force microscope (AFM) topological images of SnSe₂ with H₂ gas flow at**
48 **0.4 sccm, 0.7 sccm and 1.5 sccm. (a, c, e) AFM images of SnSe₂ crystals with different thickness. (b, d, f)**
49 **Optical images of SnSe₂ using different gas flow. Scale bars: 4 μm in (a, c, e), 50 μm in (b, f), 10 μm in (d).**

50

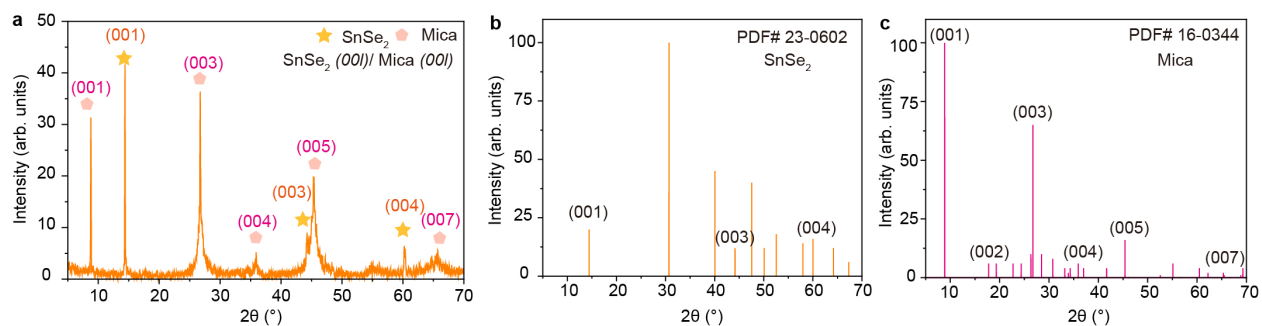
51



52

53 **Supplementary Fig. 5. Crystal structures of AA-stacked SnSe₂ flakes.** (a) Transmission electron
 54 microscope (TEM) bright field (BF) image of a typical triangular SnSe₂ nanoflake. Corresponding selected
 55 area electron diffraction (SAED) patterns taken from the three regions in a were depicted on the right
 56 panels (b-d). (e) Low-magnified scanning transmission electron microscopy (STEM) image, corresponding
 57 energy dispersive x-ray spectroscopy (EDS) elemental mapping, i.e., (f) Sn and (g) Se, and (h) EDS spectrum
 58 of AA-stacked SnSe₂. The atomic ratio of Sn and Se is determined as 1: 2. Scale bars: 200 nm in (a); 5 nm⁻¹
 59 in SAED patterns (b-d); 1 μm in (e-g).

60

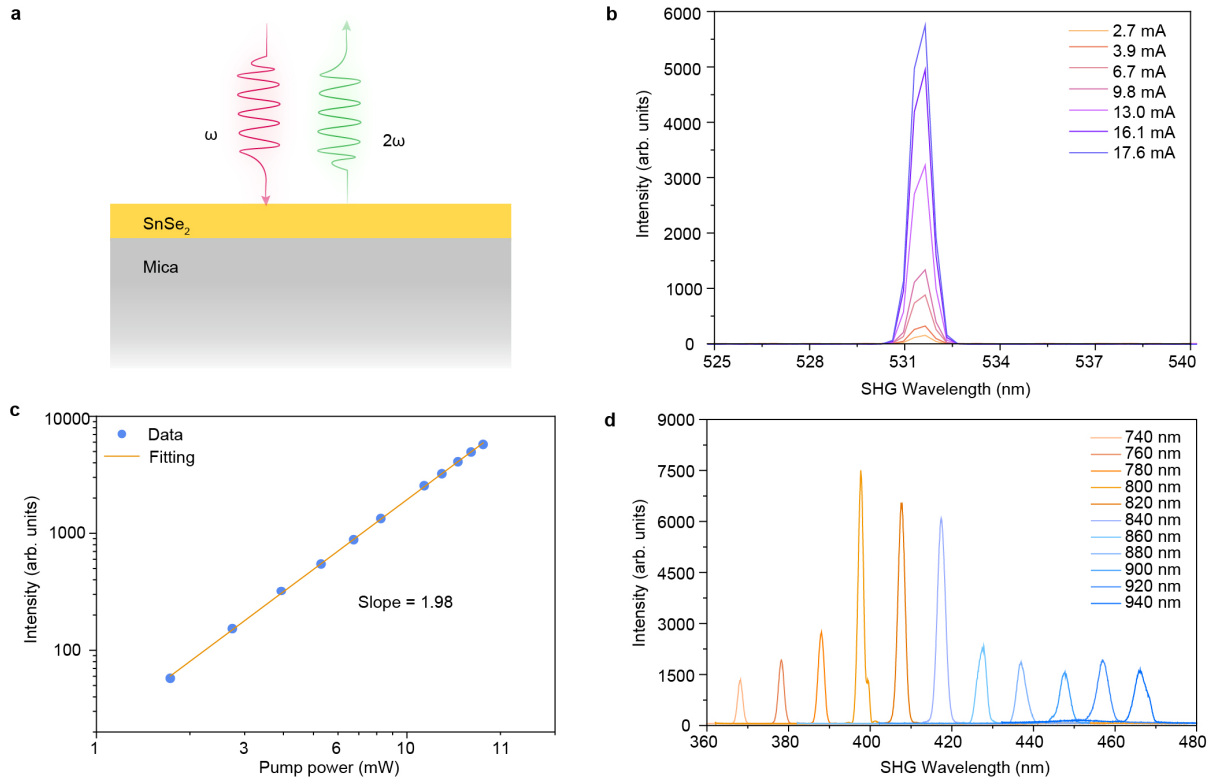


61

62 **Supplementary Fig. 6. Highly crystalline SnSe₂ flakes grown on mica substrates.** (a) X-ray diffraction (XRD)
 63 pattern of CVD-grown SnSe₂ flakes on mica substrates. The standard XRD patterns of (b) AA-stacked T-
 64 phase SnSe₂ crystal and (c) mica substrate.

65 Full 2θ scans show the appearance of sharp peaks with the angle of 2θ = 14.36°, 44.31° and 60.22°, which
 66 could be referred to as SnSe₂ (001), (003) and (004) diffraction peaks, respectively. Based on the (001)
 67 peak position, the out-of-plane lattice parameter is calculated to be 6.16 Å, which greatly resembles the
 68 lattice arrangement of reference (6.14 Å). All these results show that there is free of strain induced by the
 69 lattice mismatch between SnSe₂ and mica substrate.

70



71

72 **Supplementary Fig. 7. Second harmonic generation (SHG) of SnSe₂ (noncentrosymmetry) with an**

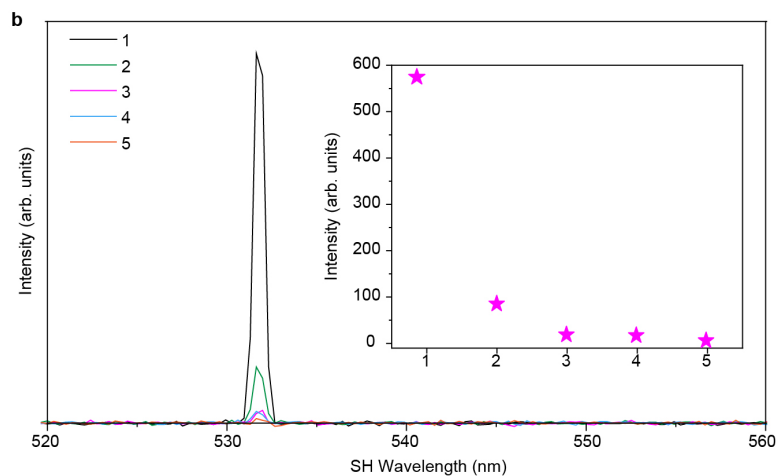
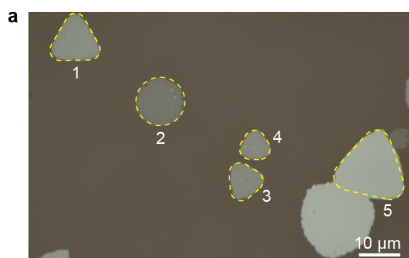
73 **excitation wavelength at 1064 nm. (a) Schematic illustration of SHG process under reflection geometry.**

74 **(b) Pump power-dependent SHG peak intensity of T-SnSe₂, which can be linearly fitted with a slope of**

75 **~1.98, confirming a second-order non-linear optics (NLO) process (c). (d) SHG spectra at different**

76 **excitation wavelengths.**

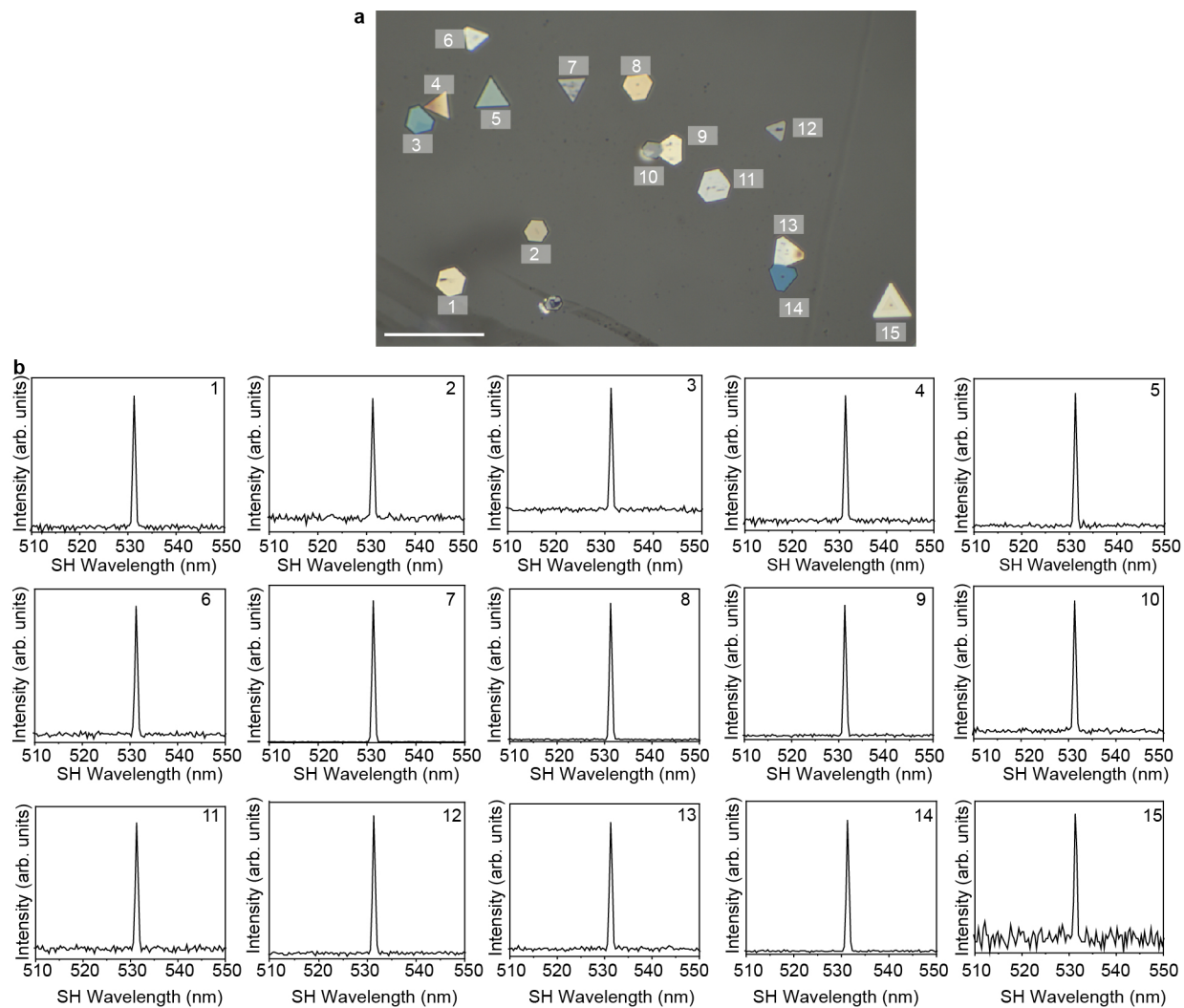
77



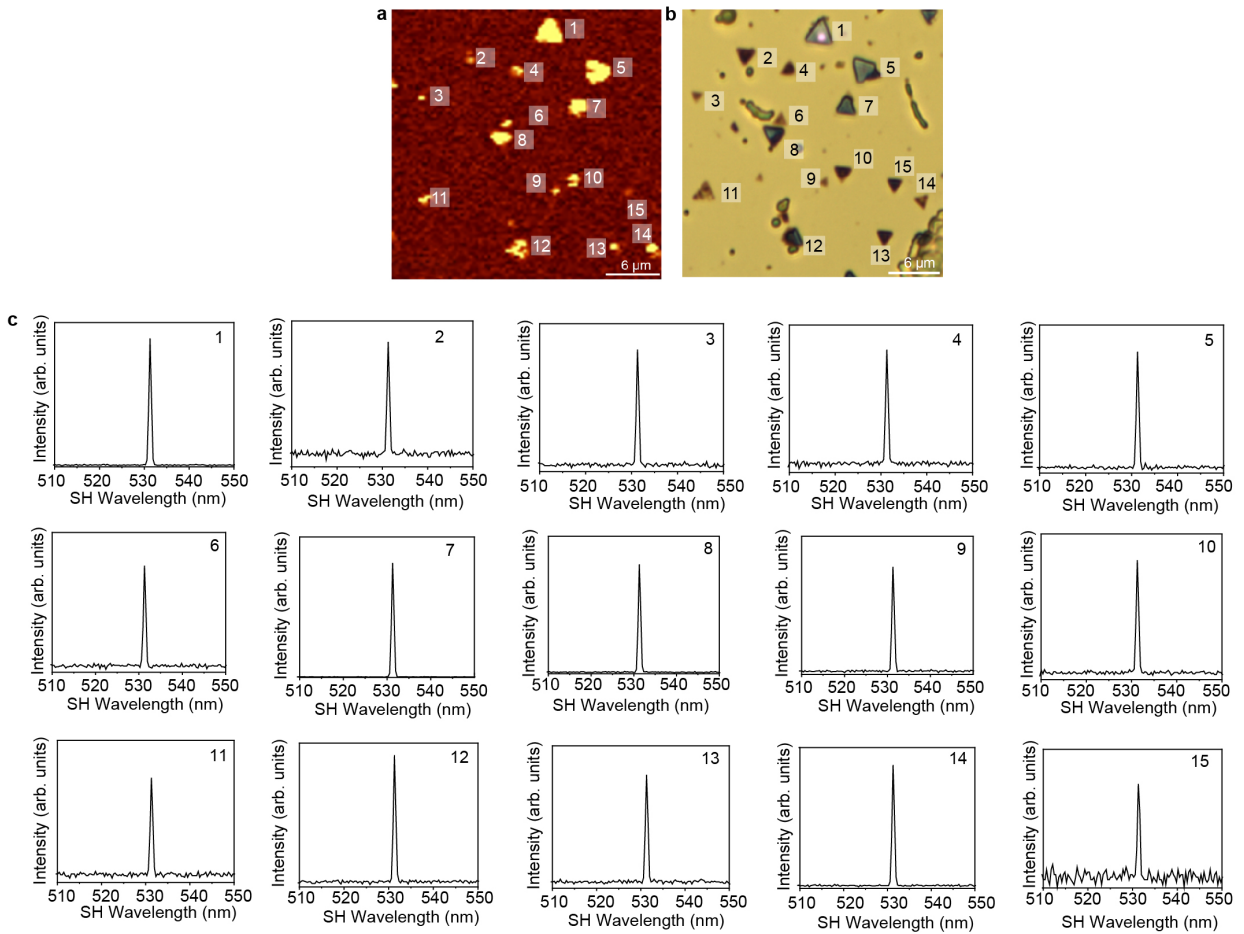
78

79 **Supplementary Fig. 8. The SHG characterizations of SnSe₂ domains with obvious SHG response.** (a) The
80 optical image of rounded triangle and rounded SnSe₂ domains. (b) The SHG intensity of SnSe₂ flakes
81 indicated in panel a. Insert image showing the corresponding SHG intensity.

82



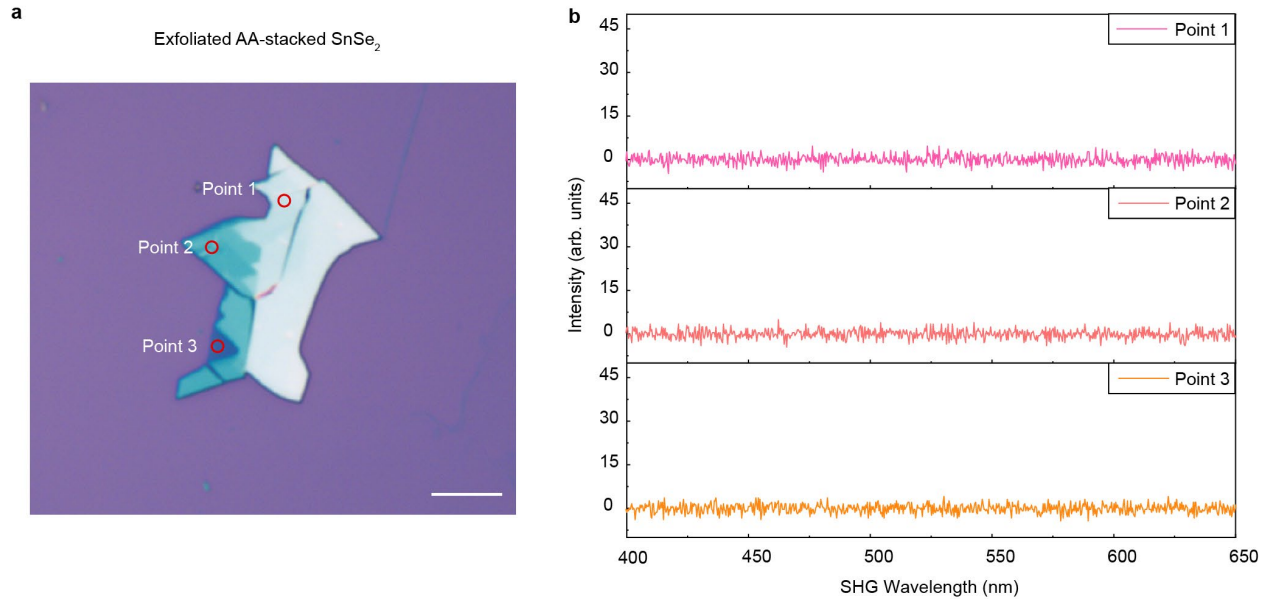
83
 84 **Supplementary Fig. 9. The SHG signals of SnSe₂ crystals with broken centrosymmetry on a mica substrate.**
 85 (a) An optical image of 15 SnSe₂ flakes dispersed across the mica substrate. (b) SHG signals obtained from
 86 all flakes, with each exhibiting a 100% SHG response. Scale bar: 20 μm in (a).



87

88 **Supplementary Fig. 10. SHG signals of SnSe₂ domains transferred onto Au film on Si substrate. (a, b) SHG**
 89 **mapping over a large area with 100% SHG signal coverage. (c) SHG results from 15 individual flakes,**
 90 **demonstrating the controllability of AB'-stacked SnSe₂ crystals.**

91



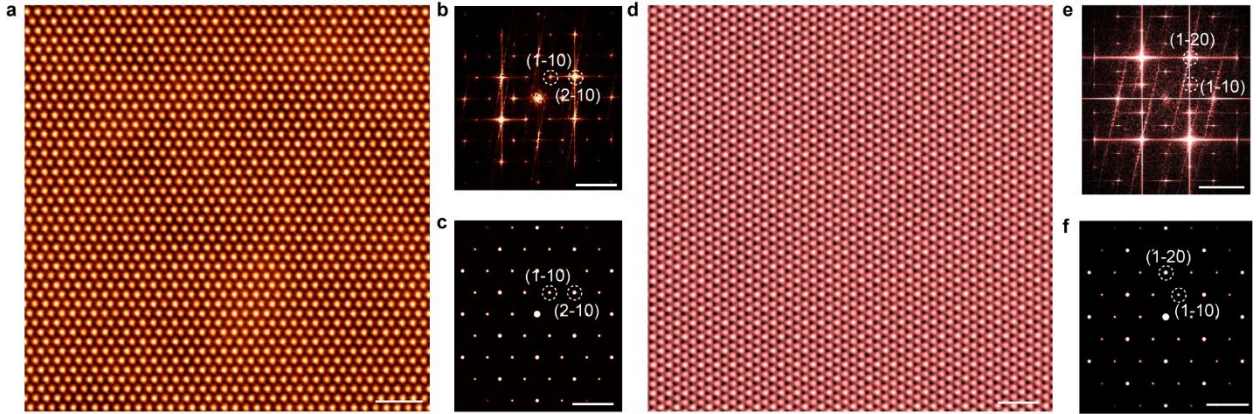
92

93 **Supplementary Fig. 11. SHG characterizations of AA-stacked SnSe₂ on SiO₂ substrate.** (a) Optical image

94 of mechanically exfoliated AA-stacked SnSe₂. (b) SHG results from the red dot regions in a. There are no

95 SHG emissions for centrosymmetric AA-stacked T-phase SnSe₂ crystals (an excitation wavelength at 1064

96 nm).



97

98 **Supplementary Fig. 12. Atomic structure analysis of SnSe₂ taking AA and AB' stacking registry. (a)**

99 Atomic-resolution annular dark field scanning transmission electron microscopy (ADF-STEM) image of AA-

100 stacked SnSe₂. (b) Corresponding fast Fourier transform (FFT) pattern of a and (c) simulated SAED pattern

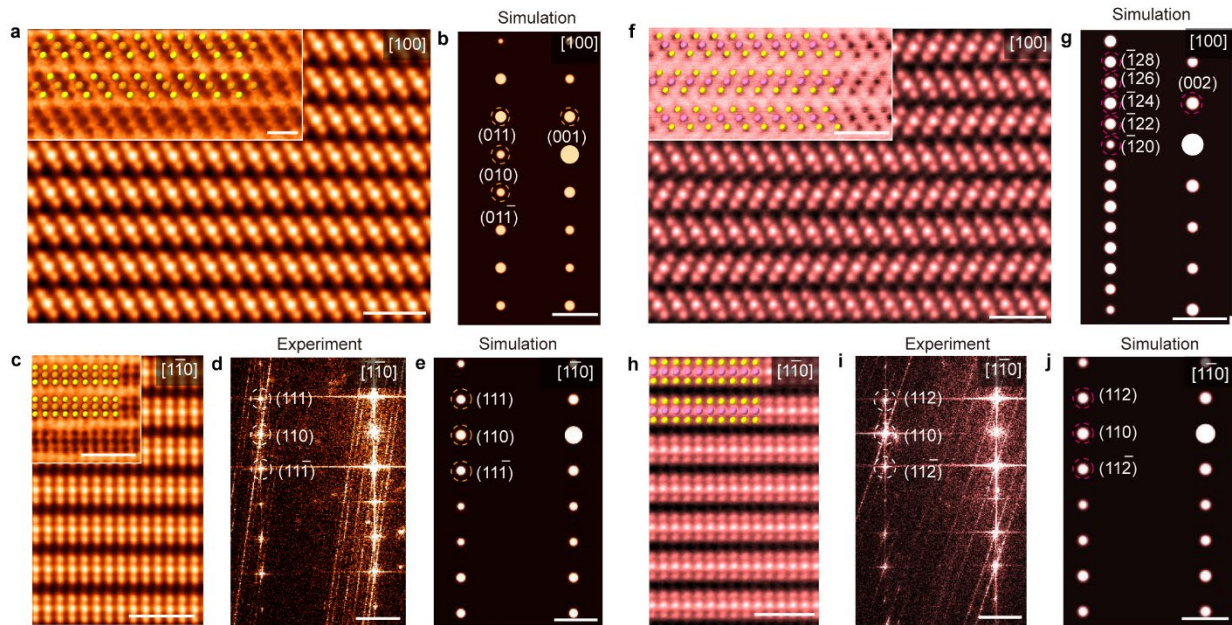
101 based on an AA-stacked SnSe₂ model. (d) Atomic resolution ADF-STEM image of AB'-stacked SnSe₂. (e)

102 Corresponding FFT pattern of d and (f) simulated SAED pattern based on AB'-stacked SnSe₂. Scale bars: 1

103 nm in (a) and (e); 5 nm⁻¹ in (b-c, f-g).

104

105



106

107 **Supplementary Fig. 13. Cross-sectional atomic structure analysis of SnSe₂ taking AA and AB' stacking**

108 **registry.** (a) Atomic resolution ADF-STEM images of AA-stacked SnSe₂ along the [100] zone axis and (b)

109 simulated SAED pattern based on an AA-stacked model. Annular bright field scanning transmission

110 electron microscopy (ABF-STEM) image taken simultaneously together with the atomic model were

111 overlaid in a. (c) Enlarged ADF-STEM image showing a well-defined AA stacking order along the [110]

112 zone axis. (d) Corresponding FFT pattern from a and (e) simulated SAED at the same region. (f) Atomic

113 resolution ADF-STEM image showing AB'-stacked SnSe₂ along the [110] zone axis and (g) simulated SAED

114 pattern. ABF-STEM image taken simultaneously together with the atomic model were overlaid in f. (h)

115 Enlarged ADF-STEM image showing a well-defined AA stacking order along the [110] zone axis. (i)

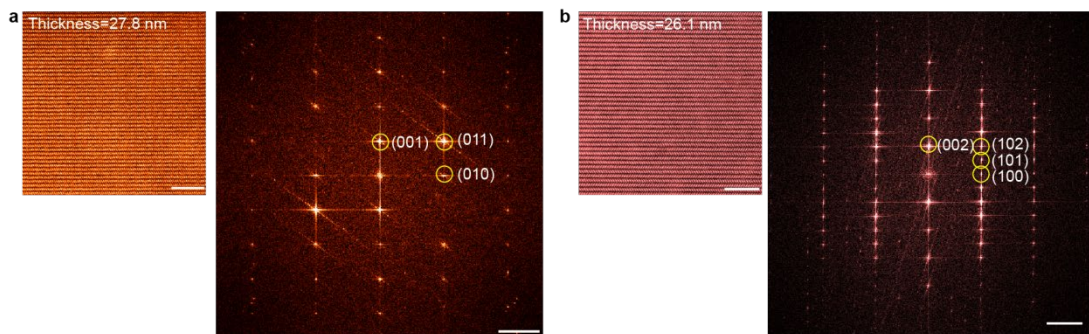
116 Corresponding FFT pattern from f and (j) simulated SAED at the same region. Scale bars: 1 nm in (a, c, f,

117 h), 1 nm; 2 nm⁻¹ in (b, d, e, g, i, j).

118

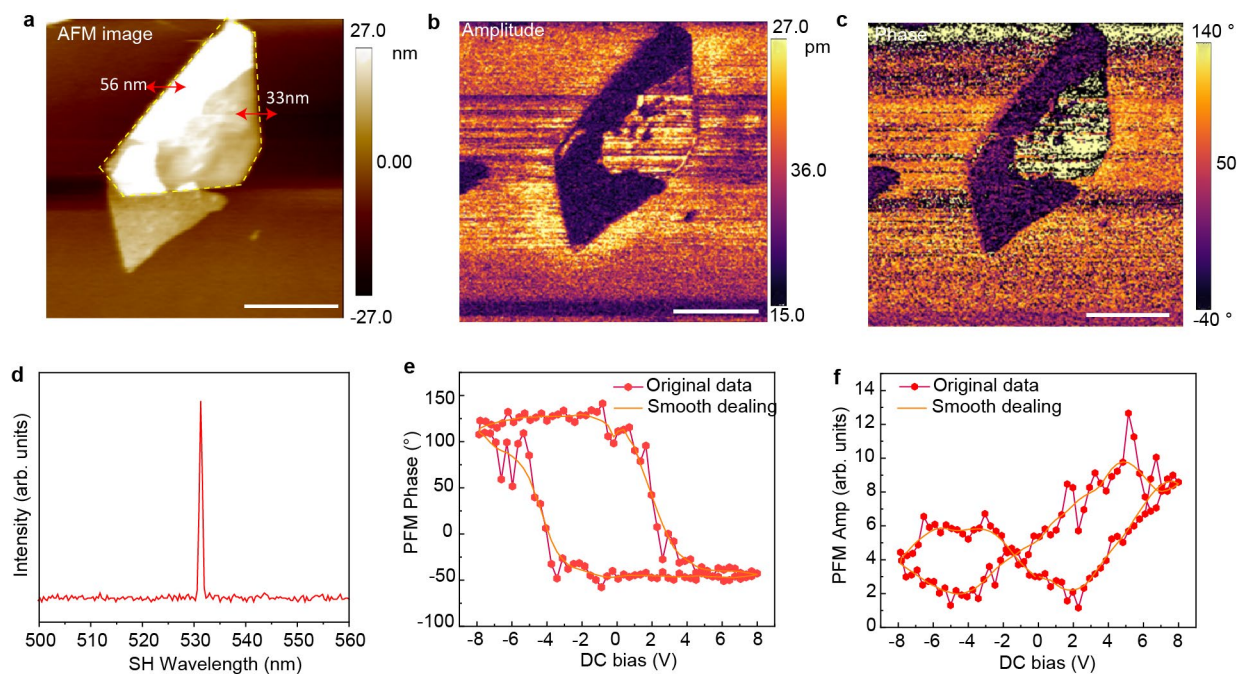
119

120



121
 122 **Supplementary Fig. 14. The ADF-STEM images and the corresponding FFT pattern over a large area. (a)**
 123 The ADF-STEM image of AA-stacked SnSe₂ with a thickness of 27.8 nm (left panel) and the corresponding
 124 FFT pattern (right panel). The FFT results are in accord with the simulated SAED pattern. (b) The ADF-STEM
 125 image of AB'-stacked SnSe₂ with a thickness of 21.6 nm and the relative FFT pattern. Analogously, the FFT
 126 results are also consistent with simulated SAED results. Scale bars: 5 nm (left panel) in (a, b); 2 nm⁻¹ (right
 127 panel).

128



129

130 **Supplementary Fig. 15. Piezoresponse force microscopy (PFM) characterizations of AB'-stacked SnSe₂**

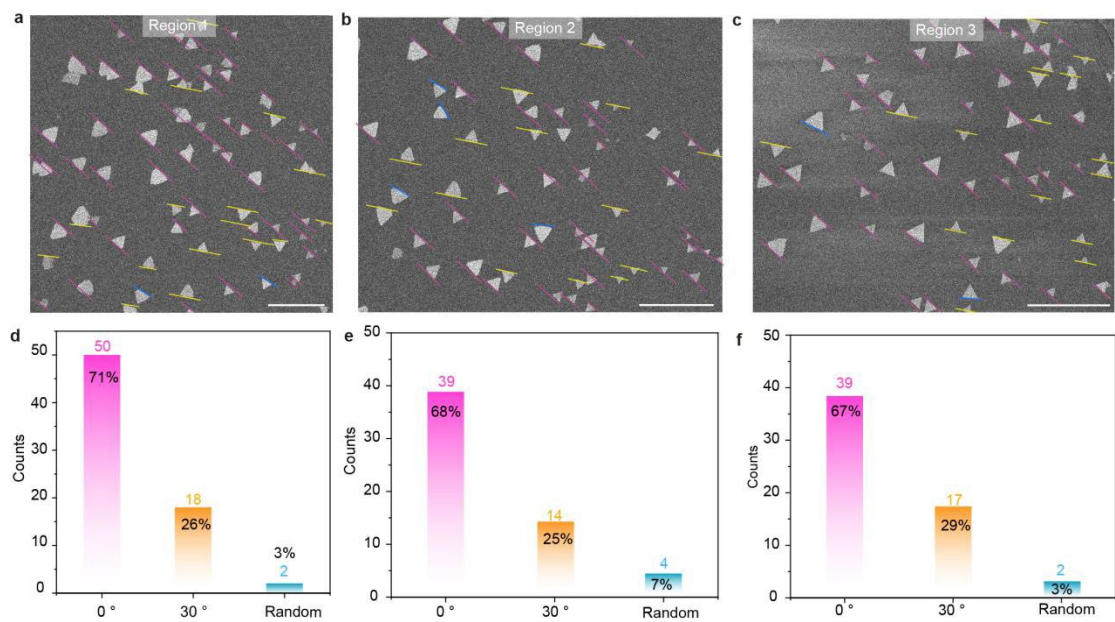
131 **crystals.** The AFM image (a), amplitude image (b) and phase image (c) of the corresponding domain

132 (labelled as yellow dashed line). (d) The domains in a with a significant SHG response. Relative PFM phase

133 hysteretic (e) and butterfly loop (f) of nanosheet with ferroelectric properties. Scale bars: 2 μm in (a-c).

134

135

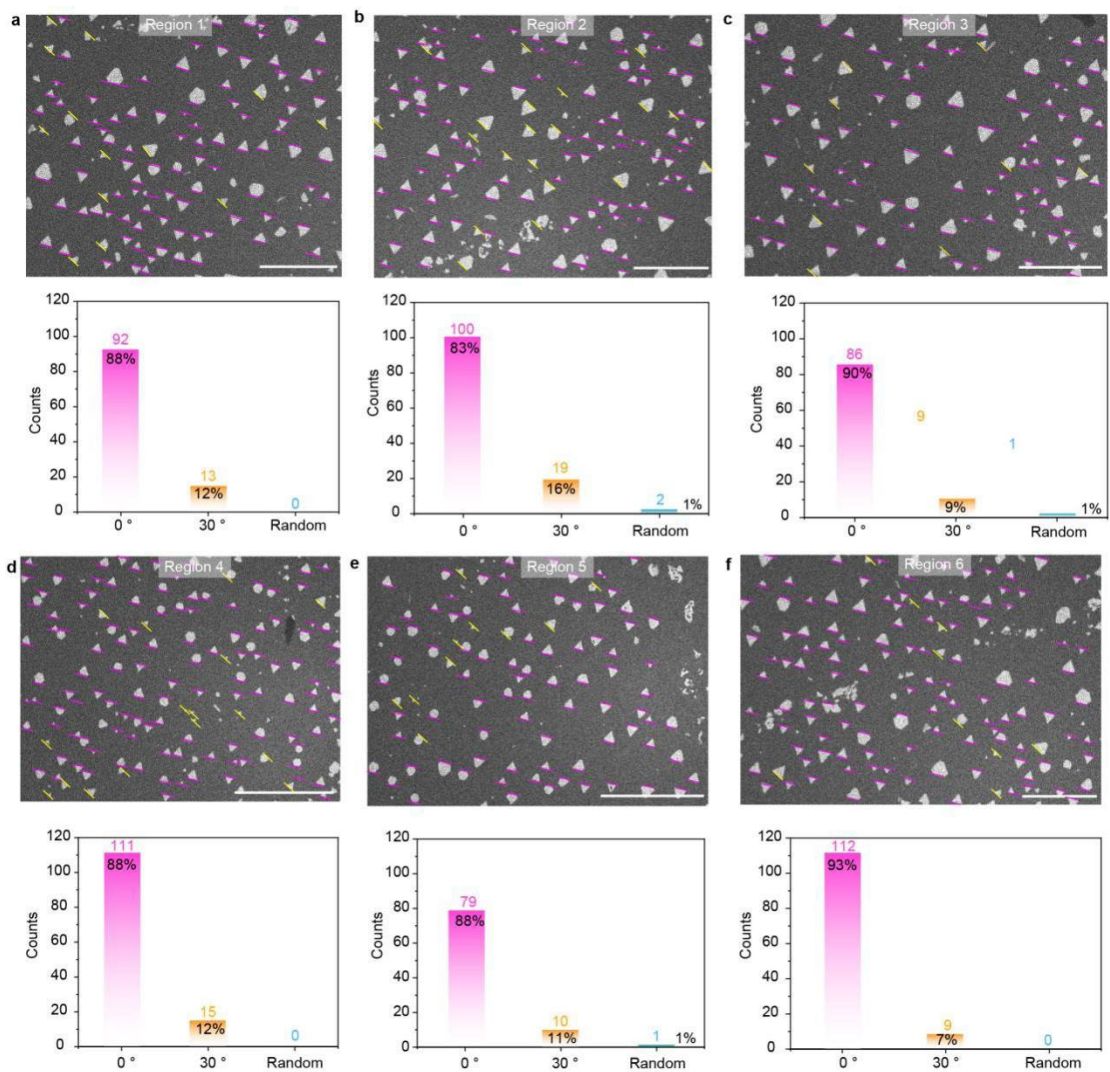


136

137 **Supplementary Fig. 16. Scanning electron microscopy (SEM) images showing SnSe₂ crystals with well-**

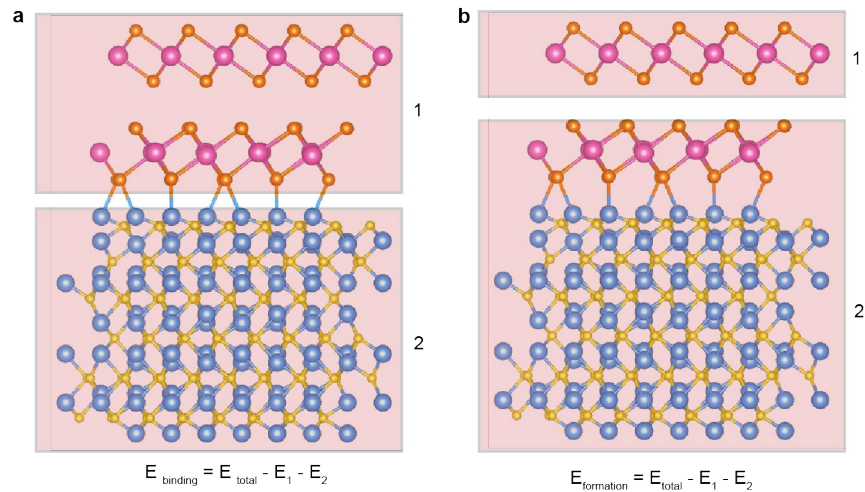
138 **defined epitaxial growth relationship (H₂ = 0.5 sccm, Ar = 20 sccm). (a-c) The orientation of SnSe₂ flakes**

139 **with 0° and 30°, respectively. (d-f) The statistical results of flakes orientations. Scale bars: 10 μm in (a-c).**



140
 141 **Supplementary Fig. 17. SEM images of SnSe₂ crystals grown at 600 °C (H₂ = 1 sccm, Ar = 30 sccm). Six**
 142 **regions are selected to count the amount of aligned SnSe₂ flakes. The alignment directions are labelled as**
 143 **0 ° (pink line) and 30 ° (yellow line), respectively. Scale bars: 50 μm in (a-c, f), 100 μm in (d, e).**

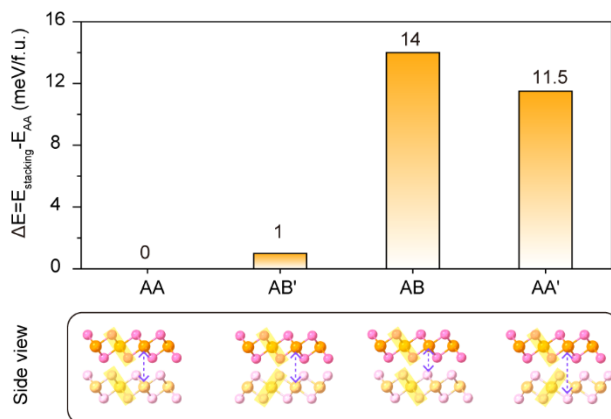
144



145

146 **Supplementary Fig. 18. The definition of binding energy and formation energy.** (a) The interlayer energy
 147 meaning the energy difference between the total energy of the supercell containing AA-stacked SnSe₂
 148 crystals (Region 1) and the sapphire substrate (Region 2). (b) schematic diagram showing the definition of
 149 formation energy.

150

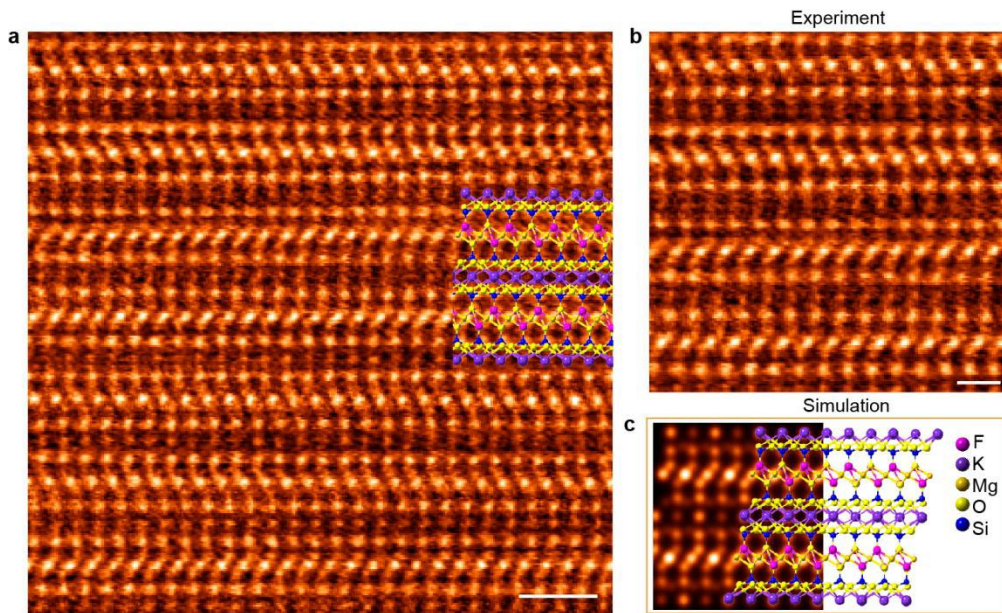


151 **Supplementary Fig. 19. Density functional theory (DFT) calculated the formation energy of various SnSe₂**
 152 **as a function of stacking registry (AA, AB', AB, and AA').**

153 The formation energy of the AA stacking order
 154 was set as 0 as the reference.

155 The binding of SnSe₂ crystals with various stacking registries through modulating the growth temperature
 156 could be ascribed to a thermodynamically stable state. To verify the hypothesis, we performed the DFT
 157 calculation to evaluate the stability. The results consistently show that the stacking energy difference is 1
 158 meV/formula unit, which can be considered as the uncertainty of DFT calculations. However, the
 159 formation energy of AA'- and AB-stacked SnSe₂ indicates their thermodynamically unstable state, which
 160 has therefore not been observed in experimental studies.

161



162

163 **Supplementary Fig. 20. The atomic structure of mica substrate.** (a, b) The ADF-STEM image of mica

164 substrate. Each sheet consists of two tetrahedral silicate layers sandwiching an octahedral sheet containing

165 aluminium or magnesium with the layers held together by positively charged potassium.

166 (c) The simulated ADF-STEM image based on mica atomic model. Scale bars: 1 nm in (a), 0.5 nm in (b).

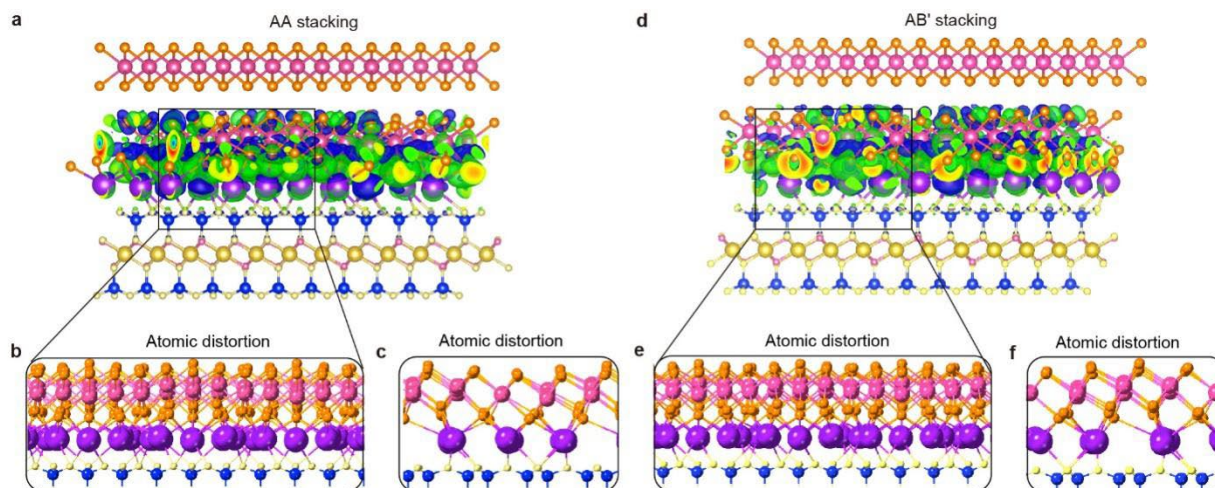
167

168

169

170

171



172

173 **Supplementary Fig. 21. Charge transfer process between SnSe₂ with AA and AB' stacking registries. (a)**

174 The differential charge density of AA-stacked SnSe₂ on mica substrate along the [1 $\bar{1}$ 0] zone axis. Enlarged

175 atomic model of **a** zooming at the interface and along the (b) [1 $\bar{1}$ 0] and (c) [100] zone axis. (c) Atomic

176 model of **a** zooming at the interface along the [100] zone axis. (d) The differential charge density of AB'-

177 stacked SnSe₂ on mica substrate along the [1 $\bar{1}$ 0] zone axis. (e, f) Enlarged atomic model of **d** zooming at

178 the interface and along the (e) [1 $\bar{1}$ 0] and (f) [100] zone axis. Notably, significant structural distortions can

179 be visualized in the zoom-in atomic models, confirming the strong interlayer charge transfer between

180 SnSe₂ and the mica substrate. As illustrated in Fig 3g, there are 10.44 e⁻ and 10.71 e⁻ transferred from mica

181 substrate to SnSe₂ with AA and AB' stacking sequences, respectively. Therefore, the AB' stacking polytype

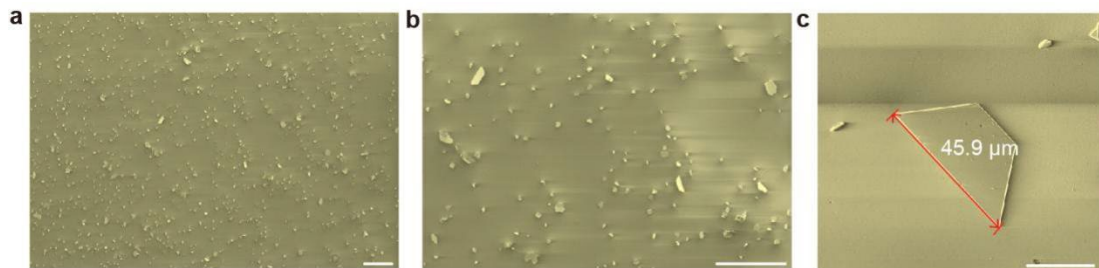
182 is more thermodynamically stable compared with AA-stacked SnSe₂.

183

184

185

186



187

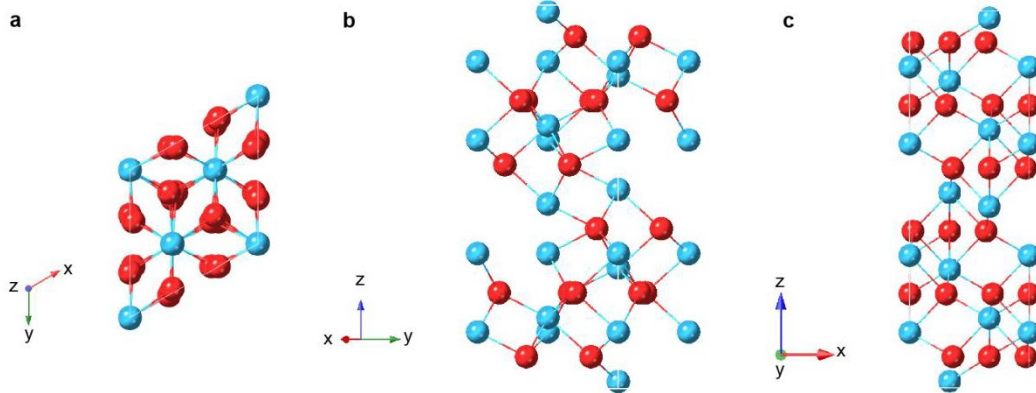
188 **Supplementary Fig. 22. SEM images of SnSe₂ crystal on sapphire substrate.** The crystals grown on the

189 sapphire substrate were free of a significant epitaxial relationship with the underlying substrate. Scale bars:

190 200 μm in (a, b); 20 μm in (c).

191

The atomic structure of sapphire



192

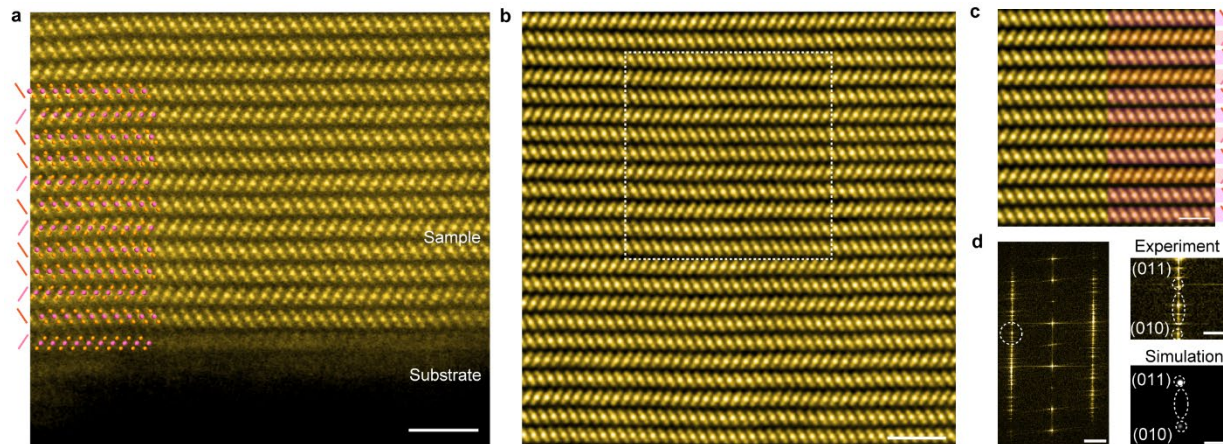
193 **Supplementary Fig. 23. The atomic structure of sapphire with lattice constant $a = b = 4.8050 \text{ \AA}$, $c =$**

194 **13.1163 \AA , $\alpha = \beta = 90^\circ$, $\gamma = 120^\circ$.** The red and blue ball corresponds to Al and O atoms, respectively. The Al

195 cations are arranged in a tightly packed lattice with O anions occupying the spaces between them, creating

196 a repeating pattern of alternating layers of Al and O atoms throughout the crystal.

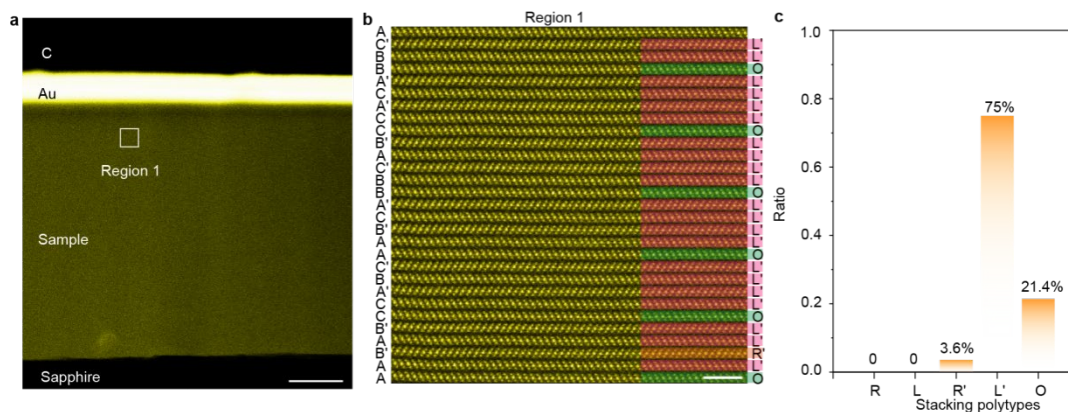
197



198

199 **Supplementary Fig. 24. Atomic structure of SnSe₂ flakes grown on sapphire substrate.** (a) Cross-sectional
 200 ADF-STEM images of SnSe₂ revealing the mixture of AA, AB', and AC' stacking orders. No well-ordered
 201 epitaxial relationship was found between the SnSe₂ crystal and the sapphire substrate. (b) The atomic
 202 structure of the inner region of as-grown SnSe₂ crystal. ADF-STEM image showing the mixed stacking
 203 structure with long periodicity. (c) The zoom-in image from the white box region in **b**. (d) The
 204 corresponding FFT patterns from **b** revealing characteristic superspots due to the coexistence of multiple
 205 stacking orders. Enlarged FFT patterns together with the simulated pattern were depicted on the right
 206 panels. Scale bars: 2 nm in (a); 1 nm in (b, c); 2 nm⁻¹ in (d).

207



209

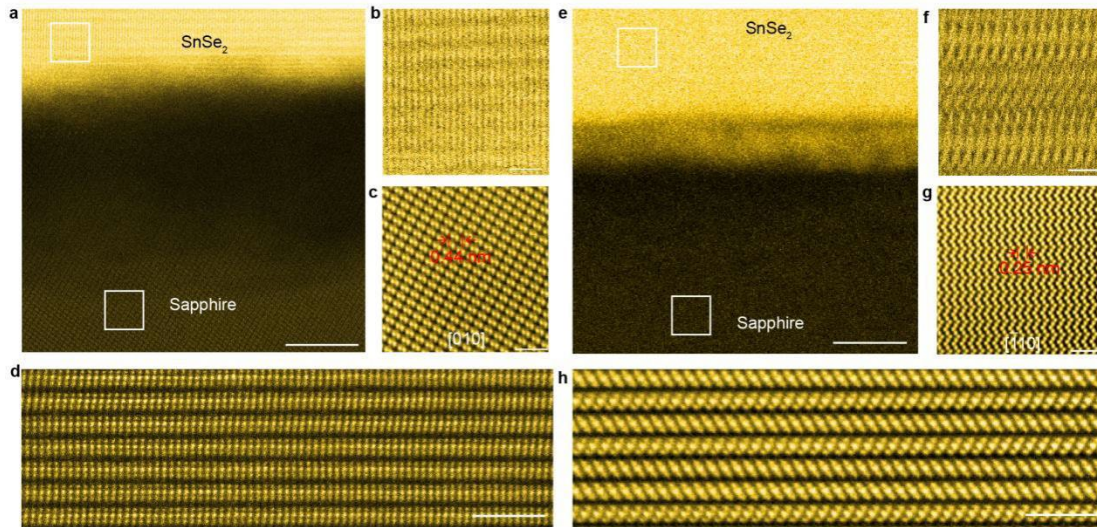
210 **Supplementary Fig. 25. The ADF-STEM image of SnSe₂ (thickness = 474 nm) on a sapphire substrate. (a)**

211 A low-magnification ADF-STEM image showing atomic configuration of SnSe₂ slabs. (b) SnSe₂ crystals with

212 mixed AA (O), AB' (R'), and AC' (L') stacking sequences. (c) Statistical analysis of the various stacking

213 polytypes of SnSe₂ crystals grown on sapphire substrates. Scale bars: 100 nm in (a); 2 nm in (b).

214



215

216 **Supplementary Fig. 26. The atomic structure at the interface between SnSe₂ and sapphire substrate. (a)**

217 ADF-STEM image showing the atomic arrangement along the sapphire [010] zone axis. (b, c) Zoom-in ADF-

218 STEM images providing SnSe₂ and sapphire substrate from **a**, respectively. (d) The arrangement of SnSe₂

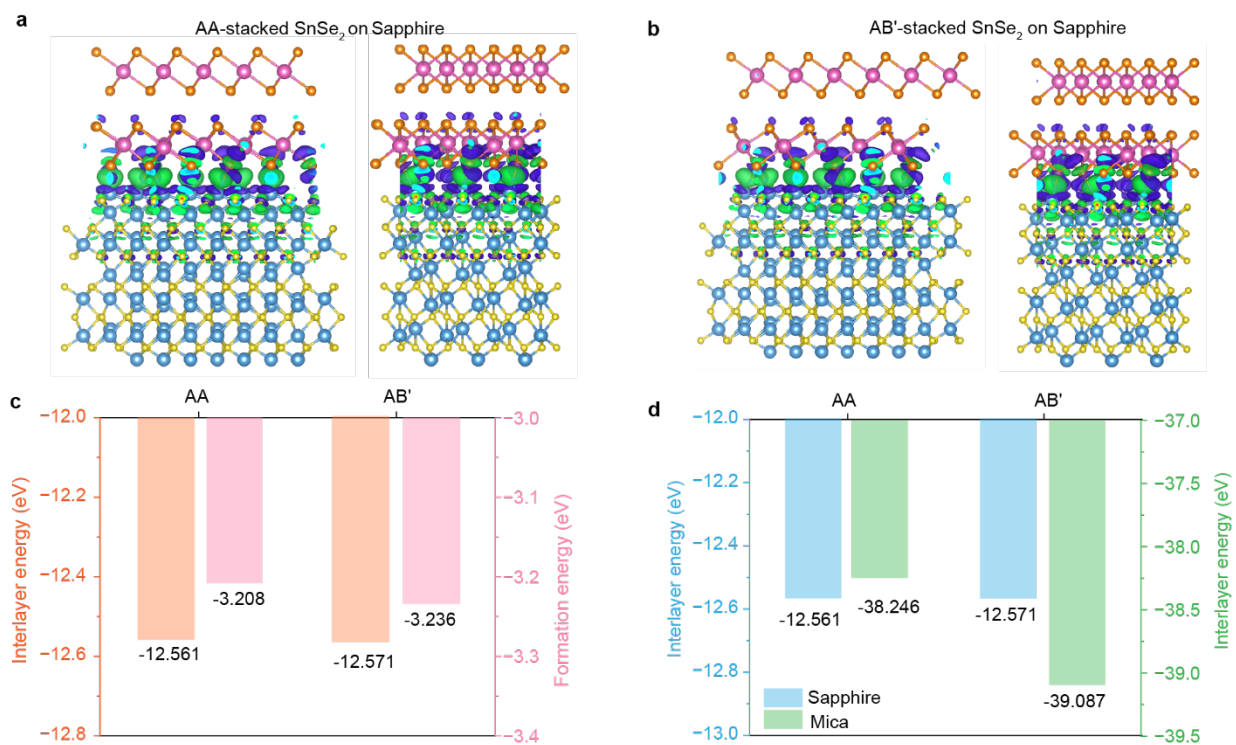
219 crystals along the [1 $\bar{1}$ 0] Zone axis. Panels **b** and **d** indicate a lack of lattice matching between SnSe₂ and

220 sapphire substrate. e, The ADF-STEM image along the [$\bar{1}$ 10] zone axis of sapphire. (f, g) Zoom-in ADF-STEM

221 images of SnSe₂ and Al₂O₃ crystals. h, Atomic structure of SnSe₂ along [100] zone axis. Scale bars: 5 nm in

222 (a, e), 1 nm in (b, c), 10 nm in (d, h), 2 nm in (f, g).

223



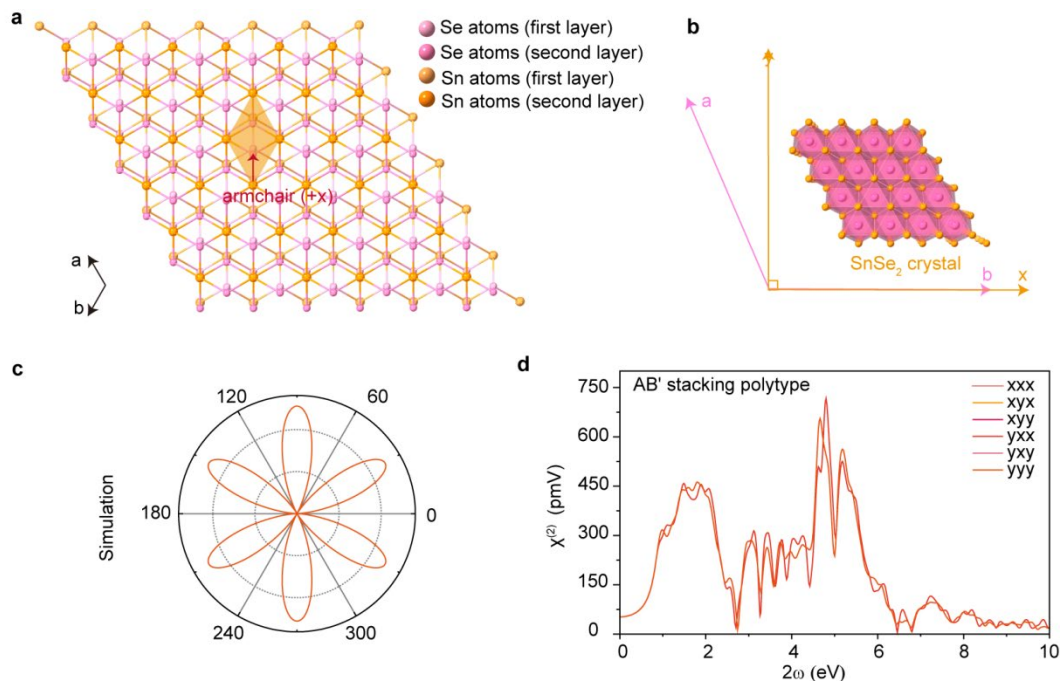
225

226 **Supplementary Fig. 27. DFT calculations of the interlayer energy and the formation energy for different**227 **stacking structures.** (a, b) The simulated ADF-STEM images derived from the DFT-optimized AA- and AB'-228 stacked SnSe₂ on the sapphire surface. The right panel illustrates the differential charge density of both229 AA-, and AB'-stacked SnSe₂ on the sapphire substrate. The area in green is the region that gained electrons,

230 and the area in purple represent those lost electrons. (c) The interlayer energy difference and the

231 formation energy difference between AA and AB'-stacked SnSe₂ on the sapphire substrate. (d) The232 interlayer energy of AA and AB'-stacked SnSe₂ on sapphire and mica substrate, respectively.

233



234

235 **Supplementary Fig. 28. Calculated SHG response of AB'-stacked SnSe₂ crystals.** (a) The schematic

236 diagram illustrating the gliding direction of the AB'-stacked SnSe₂. The arrows correspond to the gliding

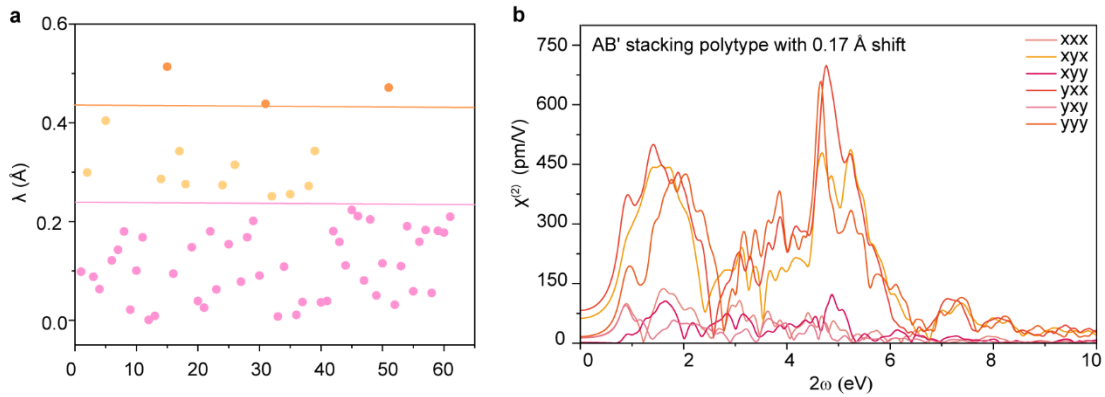
237 direction along the armchair (+x) direction. (b) The transformation from crystal coordinates (lattice

238 constant a and b) to SHG calculated coordinates (x , y). (c) Simulated polar plot pattern with six petals

239 derived from AB'-stacked SnSe₂. (d) The calculated $\chi^{(2)}$ tensor elements of the AB'-stacked SnSe₂ with

240 three nonzero tensors.

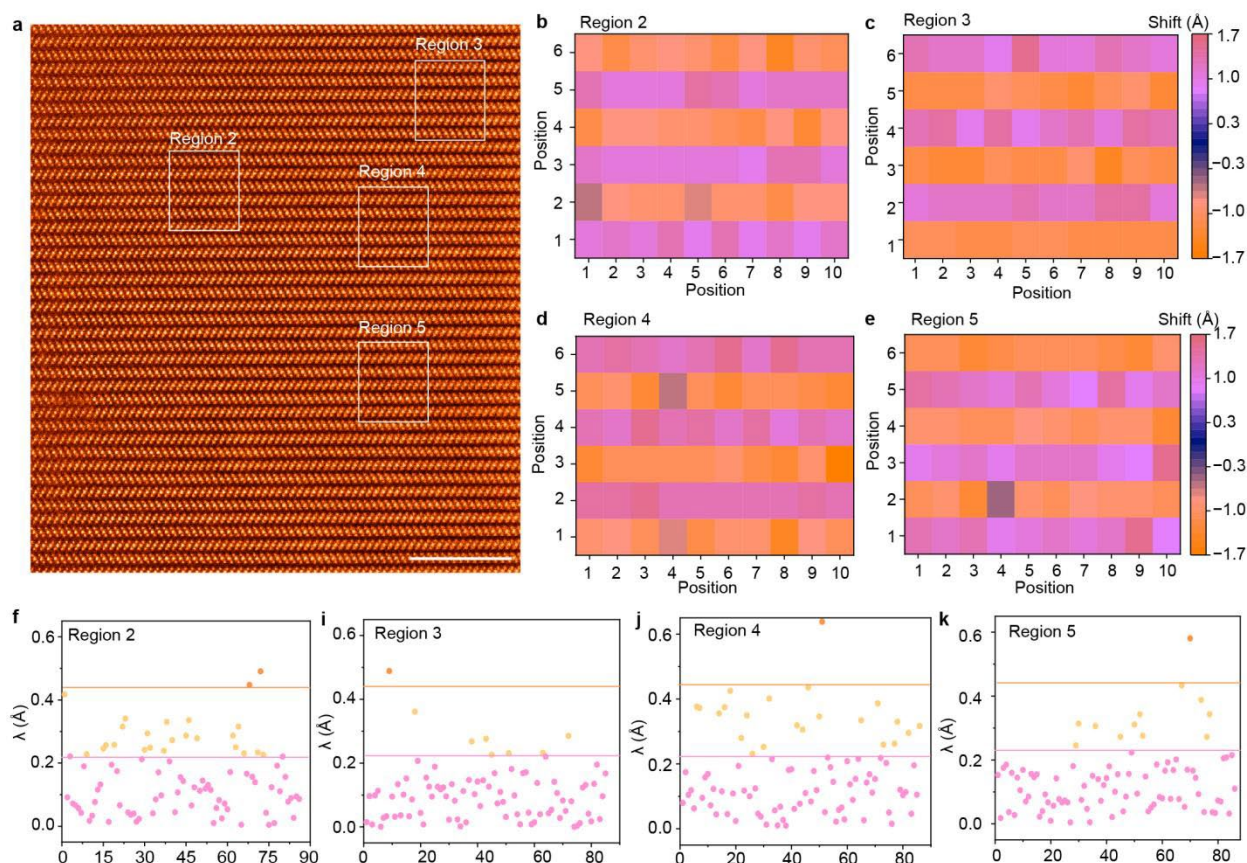
241



242

243 **Supplementary Fig. 29. The displacements of Sn atoms.** (a) The statistical result indicating a high
 244 possibility of Sn atomic displacements less than 0.22 Å based on ADF-STEM images (Fig. 4d) revealing the
 245 AB' stacking order. (b) The calculated $\chi^{(2)}$ tensor elements based on the AB'-stacked SnSe₂ with 0.17 Å
 246 displacement.

247

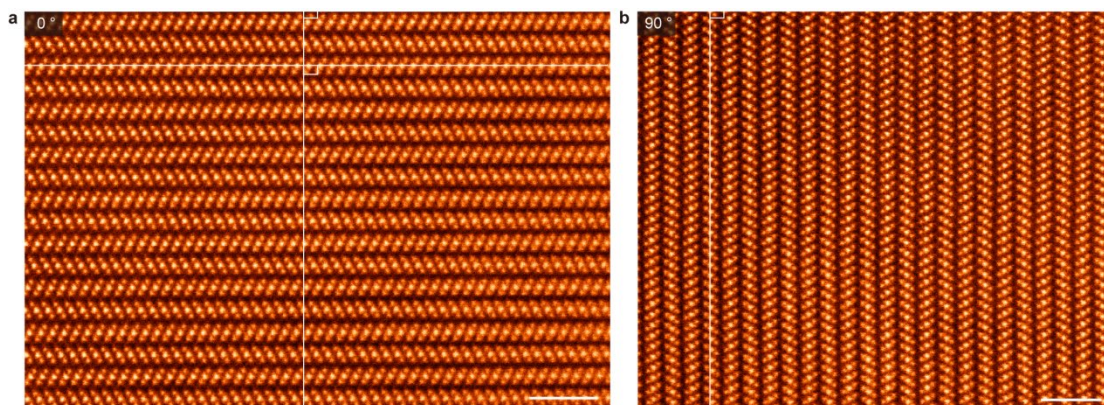


249

250 **Supplementary Fig. 30. Statistical displacements analysis of Sn atoms in AB'-stacked SnSe₂.** (a) The cross-
 251 sectional ADF-STEM image of AB'-stacked SnSe₂ with minor shifts. (b-e) Calculated Sn atom displacement
 252 maps from the white box regions 1-4 in a, respectively. (f-k) Statistical plots of the magnitude of Sn atom
 253 displacements in (f-k). The pixel size in (a) is 0.17 Å. Scale bar: 5 nm in (a).

254 Pink dots represent the displacement values less than 0.22 Å. The yellow region suggests the values are
 255 between 0.22 Å and 0.44 Å. Orange dots represent the shift values larger than 0.44 Å. From the four panels,
 256 we can infer that the atomic displacement is mainly less than 0.22 Å, consistent with the calculated
 257 slipping energy. ADF-STEM images combined with DFT calculations demonstrate that the minor
 258 displacements of a layer with respect to adjacent layers can spontaneously occur, once the energy barrier
 259 can be overcome at the given temperature.

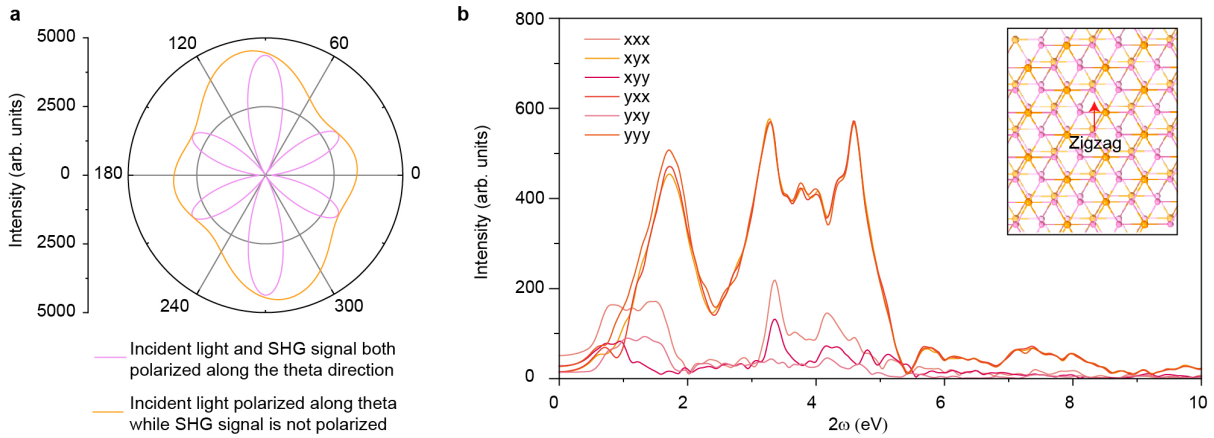
260



261

262 **Supplementary Fig. 31. ADF-STEM images of the same SnSe₂ area with different scanning angles, e.g.,**
263 **0° (a) and 90° (b).** Scale bars: 2 nm. Interlayer gliding can be observed when the scanning angle is 0°, but
264 they are absent when the scanning angle is 90°. These results confirm that the experimentally observed
265 interlayer gliding is irrelevant to the sample drift during the image acquisition.

266



267

268 **Supplementary Fig. 32. The calculated SHG results of AB'-stacked SnSe₂ with minor gliding along zigzag**

269 **direction.** (a) The calculated azimuthal SHG polarization dependence with a 1064 nm laser. The detection

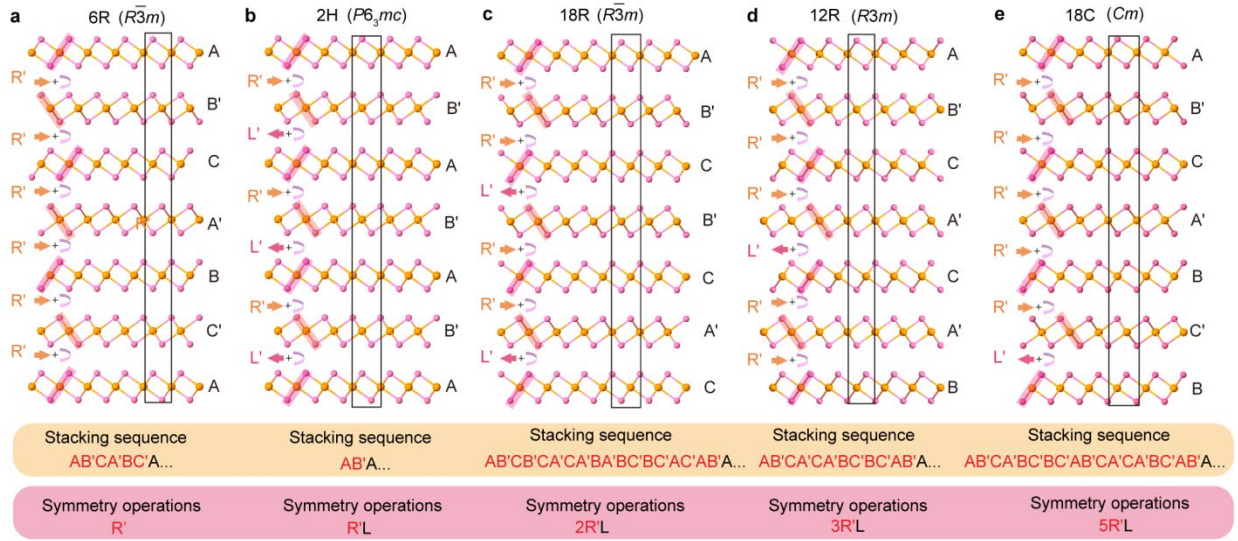
270 beams are polarized (pink) and not polarized (orange). (b) The $\chi^{(2)}$ tensor elements of the AB'-stacked

271 SnSe₂ with 0.17 Å displacement along the zigzag direction. An atomic model with interlayer gliding along

272 the zigzag gliding was depicted inset.

273

274



275

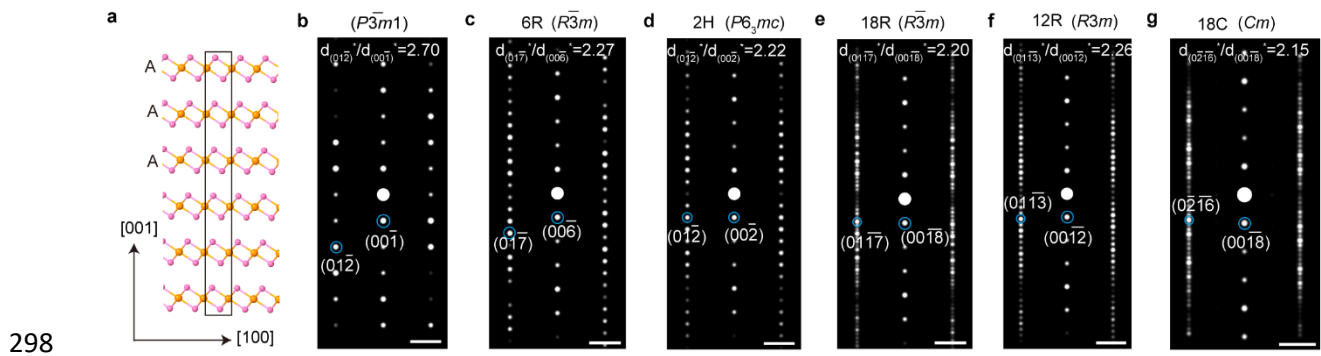
276 **Supplementary Fig. 33. The atomic models of five stacking polytypes in SnSe₂ induced by a series of**
 277 **interlayer symmetry operations.** Atomic structures of SnSe₂ displaying 6R ($R\bar{3}m$) (a), 2H ($P6_3mc$) (b), 18R
 278 ($R\bar{3}m$) (c), 12R ($R3m$) (d), and 18C (Cm) (e), space group. The in-plane displacement operation is
 279 represented as an orange arrow and the interlayer inversion operation is labelled by a pink arrow. The Sn
 280 and Se atoms are highlighted in orange and pink, respectively.

281 Firstly, all structures feature interlayer gliding and interlayer mirror symmetry operations between two
 282 adjacent SnSe₂ layers, and the major symmetry operations come from the crystallographic direction of
 283 the interlayer gliding. As illustrated in Fig. 5a-b, the interlayer gliding along the [120] direction from A to
 284 B is defined as an R operation, while the gliding along $[\bar{1}20]$ direction from A to C is termed as L. The
 285 operation in AB' stacking structure, in which the first SnSe₂ slabs glide against the bottom layer as well as
 286 rotating 180° was defined as R'. And the glide along $[\bar{1}20]$ direction with inversion symmetry is regarded
 287 as L'.

288 As for the 6R stacking registry, the bottom layer of two adjacent layers always translates $\frac{1}{\sqrt{3}}a$ along the
 289 [120] direction relative to the upper layer, resulting in an AB'CA'BC' sequence with a periodic unit
 290 containing six layers (Supplementary Fig. 33a). Besides, another stacking sequence namely 2R'L' is

291 observed with a periodicity of 18 layers, featuring a much lower symmetry structure, which belongs to
292 $\bar{R}3m$ (Supplementary Fig. 33c). Significantly, 3R'L' and 5R'L' stacking landscapes, with a unit cell of 12
293 layers and 18 layers respectively (Supplementary Fig. 33d and e), also be observed. The corresponding
294 space groups are labeled as R3m and Cm, respectively. The stacking polytypes of 12R exhibit broken
295 centrosymmetric character, demonstrating the relationship between the crystal symmetry and interlayer
296 behaviors.

297



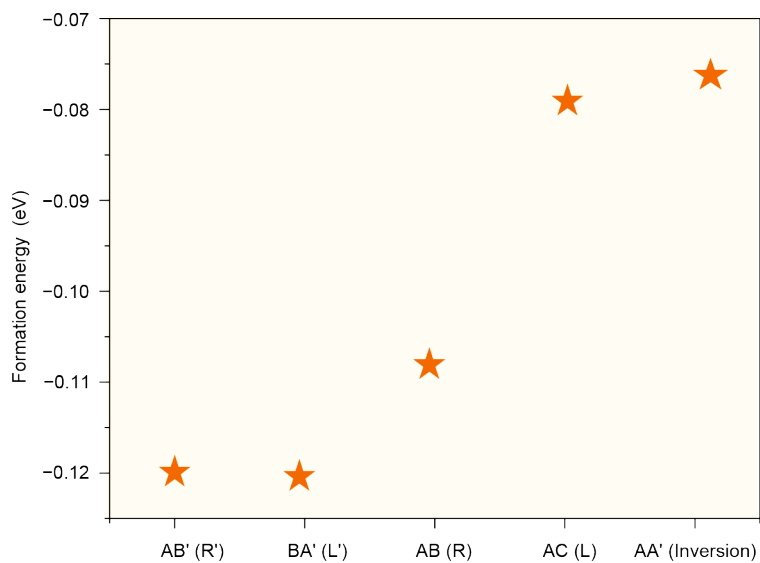
299 **Supplementary Fig. 34. The diffraction analysis of the as-grown SnSe₂ with an atlas of stacking polytypes.**

300 (a) Atomic model of AA-stacked SnSe₂ along [010] zone axis. The simulated electron diffraction patterns
 301 of $P\bar{3}m1$ (b), 6R (c), 2H (d), 18R (e), 12R (f) and 18C (g) along the [100] direction. Scale bars: 2 nm⁻¹.

302 The interlayer gliding disrupts the crystal symmetry of SnSe₂ crystals, thus affecting the periodicity and
 303 intensity of diffraction patterns. Compared with standard AA-stacked SnSe₂, the FFT patterns of
 304 AB'CA'BC'A-stacked SnSe₂ with $R\bar{3}m$ space group reveals an additional set of diffusive Bragg spots
 305 suggesting long-range ordering in AB'CA'BC'A-stacked SnSe₂ (Supplementary Fig. 34b-g).

306

307



308

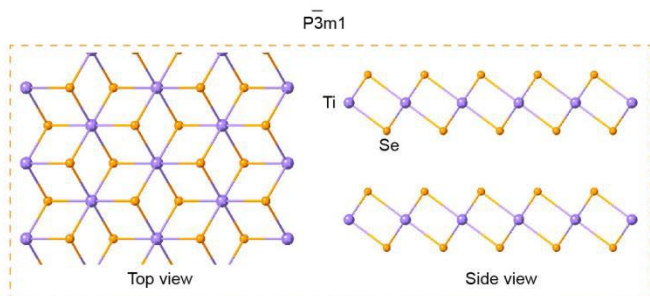
309 **Supplementary Fig. 35. The calculated formation energy of the five symmetric operations without the**
310 **consideration of mica substrate.**

311 The energy of AB' and BA' stacking sequences are thermodynamically equivalent and represent the most
312 stable stacking polytypes.

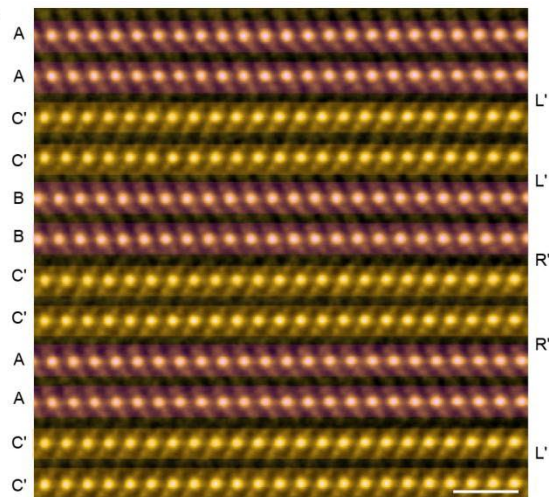
313

314

a T-TiSe₂



b



315

316 **Supplementary Fig. 36. Cross-sectional analysis of CVD-grown TiSe₂ crystals.** (a) Atomic model of the
317 intrinsic AA-stacked TiSe₂ from the top (left panel) and side view (right panel). (b) ADF-STEM image of T-
318 phase TiSe₂ with an AAC'C'BBC'C' stacking sequence. Scale bar: 1 nm.

319

320 2. Supplementary Table 1-10

Stacking orders	E (eV)*	E (eV/f.u.)	ΔE (meV/f. u.)	Formation energy (eV/f.u.)
AB'/BC'/CA'	-24.773	-12.386	1	-0.121
AC'/BA'/CB'	-24.773	-12.386	1	-0.121
AA'/BB'/CC'	-24.774	-12.387	0	-0.122
AB/BC/CA	-24.746	-12.373	14	-0.108
AC/BA/CB	-24.689	-12.344	43	-0.079
AA'/BB'/CC'	-24.749	-12.375	11.5	-0.110

321 * Total energy E (eV); f. u.= formula unit

322 **Supplementary Table 1.** The DFT calculated formation energies of SnSe₂ as a function of stacking order

323 without accounting for the substrate effect.

324

325

Work function (eV)	AA stacking	AB' stacking
Mica	3.049	3.0512
SnSe ₂	5.888	5.9149

326 **Supplementary Table 2.** DFT results showing work functions of mica crystal, AA- and AB'-stacked SnSe₂
327 crystals with the mica/SnSe₂ system.

328

329

	Total energy (eV)	Substrate energy (eV)	SnSe ₂ energy (eV)	Interlayer energy (eV)
AA-stacked SnSe ₂ /Sapphire	-2212.726	-1903.664	-296.501	-12.561
AB'-stacked SnSe ₂ /Sapphire	-2213.862	-1904.770	-296.521	-12.571
AA-stacked SnSe ₂ /mica	-3283.314	-2457.692	-787.375	-38.246
AB'-stacked SnSe ₂ /mica	-3284.557	-2458.615	-786.855	-39.087

330 **Supplementary Table 3.** The interlayer energy of AA- and AB'-stacked SnSe₂ on sapphire and mica
331 substrate.

332

Work function (eV)	AA stacking	AB' stacking
Sapphire	6.040	6.154
SnSe ₂	5.606	5.921

333 **Supplementary Table 4.** Work functions of sapphire, AA-stacked and AB'-stacked SnSn₂ crystals in
334 sapphire/SnSe₂ system.

335

336

337

	Formation energy (eV)
AA-stacked SnSe ₂ /Sapphire	-3.208
AB'-stacked SnSe ₂ /Sapphire	-3.236
AA-stacked SnSe ₂ /Mica	-7.949
AB'-stacked SnSe ₂ /Mica	-8.064

338 **Supplementary Table 5.** The formation energy of AA- and AB'-stacked SnSe₂ on sapphire and mica
339 substrate.

340

	Average (Å)	Maximum (Å)	Minimum (Å)	$0.22 \leq \lambda \text{ (Å)} \leq 0.44$	$\lambda \text{ (Å)} < 0.44$
Region 1	0.173	0.554	0.001	26.3%	4.9%
Region 2	0.145	0.451	0.001	16.3%	1.2%
Region 3	0.118	0.449	0.000	16.3%	1.2%
Region 4	0.184	0.678	0.003	16.3%	3.5%
Region 5	0.132	0.540	0.000	16.3%	1.2%
Simulation	Error: 0.0095%				

341 **Supplementary Table 6.** Calculated gliding magnitude λ based on ADF-STEM images (Fig. 4d and

342 Supplementary Fig. 30b-e).

343 More than half of the atoms display displacements smaller than 0.22 Å, and a few atomic displacements

344 reach 0.68 Å, which matches well with the calculation of interlayer slipping energy.

345

Slip distance (Å)	E (eV)	ΔE (meV/f. u.)
0 (AC')	-24.766	0.000
0.22	-24.763	1.543
0.44	-24.757	4.493
0.66	-24.750	7.840
0.88	-24.745	10.348
1.10 (AA')	-24.749	8.721
1.32	-24.745	10.376
1.54	-24.750	7.939
1.76	-24.757	4.768
1.92	-24.763	1.614
2.20 (AB')	-24.766	0.009

346 **Supplementary Table 7.** DFT calculated the gliding barrier of AC'-stacked SnSe₂ gliding along the [120]
347 for 2.20 Å distances.

348

349

	Total energy (eV)	Interlayer energy (eV)	Formation energy (eV)
BA'-stacked SnSe ₂ /mica (L')	-3283.496	-38.486	-7.708
AB'-stacked SnSe ₂ /mica (R')	-3284.557	-39.087	-8.604

350 **Supplementary Table 8.** The interlayer energy as well as formation energy between R' and L' operations
351 after taking into account of mica substrate.

Stacking sequence	SnI ₂ temperature	Gas flow (Ar)	Gas flow (H ₂)
AA stacked SnSe ₂	320 °C	20 sccm	0.4 sccm
AB' (2H) stacked SnSe ₂	340 °C	20 sccm	0.4 sccm
6R stacked SnSe ₂	340 °C	40 ~ 80 sccm	0.8 sccm
18R stacked SnSe ₂	340 °C	40 ~ 80 sccm	0.8 sccm
12R stacked SnSe ₂	340 °C	40 ~ 80 sccm	0.8 sccm
18C stacked SnSe ₂	340 °C	40 ~ 80 sccm	0.8 sccm

352 **Supplementary Table 9.** The detailed growth conditions of SnSe₂ crystals with different stacking sequences.

353

354

	Symmetry operations	$\chi_{xxx}^{(2)}$	$\chi_{xyx}^{(2)}$	$\chi_{xyy}^{(2)}$	$\chi_{yxx}^{(2)}$	$\chi_{yyx}^{(2)}$	$\chi_{yyy}^{(2)}$
6R ($R\bar{3}m$)	R'	0.057	0.113	0.016	0.065	0.026	0.247
2H ($P6_3mc$)	R'L'	0.003	242.471	9.70×10^{-4}	242.586	0.003	244.358
18R ($R\bar{3}m$)	2R'L'	0.002	0.035	0.002	0.046	0.002	0.110
12R ($R3m$)	3R'L'	0.003	61.809	0.001	61.743	0.002	61.566

355

356 **Supplementary Table 10.** Calculated six components $\chi^{(2)}$ of various stacking polytypes for T-phase SnSe₂.

357 The SnSe₂ crystals with P6₃mc and R3m polytypes exhibit nonzero SHG response with an exciting light at

358 1064 nm.

359

360

362 **Supplementary Note 1: DFT calculations**

363 DFT calculations were performed using the generalized gradient approximation for the exchange-
364 correlation potential, the projector augmented wave method^{1,2}, and a plane-wave basis set as
365 implemented in the Vienna ab initio simulation package³. The Perdew-Burke-Ernzerhof functional were
366 considered at the DFT-D3 level³.

367 For the calculation of AA and AB'-stacked SnSe₂ without considering the existence of substrate, we
368 employed a kinetic energy cut-off of 600 eV for the plane-wave basis set to perform geometric and
369 interlayer energy calculations. A k-mesh of 21 × 21 × 1 was adopted to sample the first Brillouin zone. All
370 atoms were relaxed until the residual force per atom reached $5 \times 10^{-3} \text{ eV \AA}^{-1}$ and the energy convergence
371 criteria were set to $1 \times 10^{-5} \text{ eV}$.

372 Considering the effect of substrate on the interlayer energy of AA and AB'-stacked SnSe₂ crystals, the
373 calculation was performed using a kinetic energy cut-off of 450 eV for the plane-wave basis set. The k-
374 mesh was set to 9 × 5 × 5 to sample the first Brillouin zone. In this case, the relaxation of all atoms in the
375 unit cell was allowed until the residual force per atom reached $2 \times 10^{-2} \text{ eV \AA}^{-1}$ and the energy convergence
376 criteria was $1 \times 10^{-5} \text{ eV}$. Notably, the supercells used in this calculation were $4 \times 4\sqrt{3}$ SnSe₂ and 3×3
377 mica, with a mismatch of 4 % tensile strain for mica. Additionally, $2\sqrt{3} \times 2\sqrt{3}$ SnSe₂ with 3×3 sapphire,
378 resulting in a mismatch of 8 % compressive strain for sapphire.

379

380

381 **Supplementary Note 2: The calculation results of SnSe₂ crystals on sapphire substrate.**

382 The typical c-plane oriented sapphire generally exhibits an aluminium (Al) surface termination, as depicted
383 in Supplementary Fig. 23. Experimentally, SnSe₂ crystals did not exhibit perfect epitaxial alignment with
384 the sapphire substrate under the same growth conditions (Supplementary Fig. 22). Specifically, ADF-STEM
385 imaging revealed a significant off-axis deviation of sapphire substrate when SnSe₂ was aligned along its
386 principal axis (Supplementary Fig. 26). For SnSe₂ crystals with a thickness of 474 nm, we qualified the
387 stacking behaviors, finding that 75% exhibited BA' (L') stacking behaviors, 3.6 % with AB' (R') stacking
388 orders and 21.4 % had intrinsic stacking slabs (Labelled as O).

389 Bader charge analysis further revealed that the charge transfer between the sapphire substrate and SnSe₂
390 was significantly weakened compared to that observed with mica (2.03 e⁻ for AA stacked SnSe₂ and 2.02
391 e⁻ for AB'-stacked SnSe₂). Furthermore, the work function of sapphire is approximately 6.0 eV, closely
392 matching that of SnSe₂, whereas the variation in formation energy across different substrates can reach
393 up to 4.0 eV, underscoring the critical influence of substrate choice in the material growth process
394 (Supplementary Table 4).

395

396

397

398

399 **Supplementary Note 3: ADF-STEM image analysis details**

400 Quantitatively, we calculated the interlayer shifts (λ) using a customized Python script. The λ is defined as
401 the horizontal distance between adjacent Sn atoms in neighboring layers. On the grounds of this, we found
402 that the λ ranges from 0 to 0.55 Å. Meanwhile, there are no significant gliding preferences along the -x or
403 +x directions (Supplementary Table 3). In parallel, the other four regions analyzed unexceptionally display
404 comparable behaviors, highly indicating a disorder interlayer gliding manner for adjacent SnSe₂ slabs
405 (Supplementary Fig. 17). The error of customized scripts, based on the simulated AB'-stacked SnSe₂, has
406 been quantitatively measured, with a negligible value (0.0095%) (Fig. 4c). ADF-STEM images captured at
407 different scan rotation angles of 0° and 90° eliminate the influence of image drift (Supplementary Fig.
408 18).

409

410

411 **Supplementary Note 4: Strategy for the controlled synthesis of diverse SnSe₂ stacking registries with**
412 **highly ordered superlattices.**

413 During the synthesis of SnSe₂, we adjusted the Ar gas flow between 40 - 80 sccm to modulate the
414 nucleation and growth dynamics, aiming to reconfigure SnSe₂ slabs. In principle, the gas flow rate should
415 be suitable to give viscous laminar flow to ensure a homogeneous growth environment during the
416 reaction process. However, there is always a velocity gradient of gases in the growth chambers, and
417 decreases to zero when near the substrate, presenting a stagnant layer⁴. Choosing the high-rate gas flow
418 is more likely to generate turbulence, which is concluded from the definition of the Reynolds coefficient.
419 Meanwhile, the temperature gradient inside the furnace also accelerates the formation of turbulence.
420 During the process, the collision of the atoms will be enhanced, which breaks the thermodynamic
421 equilibrium and transforms the system into kinetic dominance^{5,6}. The CVD growth process is generally
422 complicated involving the sublimation and diffusion process of multiple precursors, maintaining the
423 repeatability of 2D materials is still a big challenge⁷. Molecular beam epitaxy (MBE), owing to the high
424 accuracy of controlling growth parameters, facilitate the precise manipulation of kinetic and
425 thermodynamic behaviors to regulate the crystal symmetry in a variety of 2D materials⁸.

426

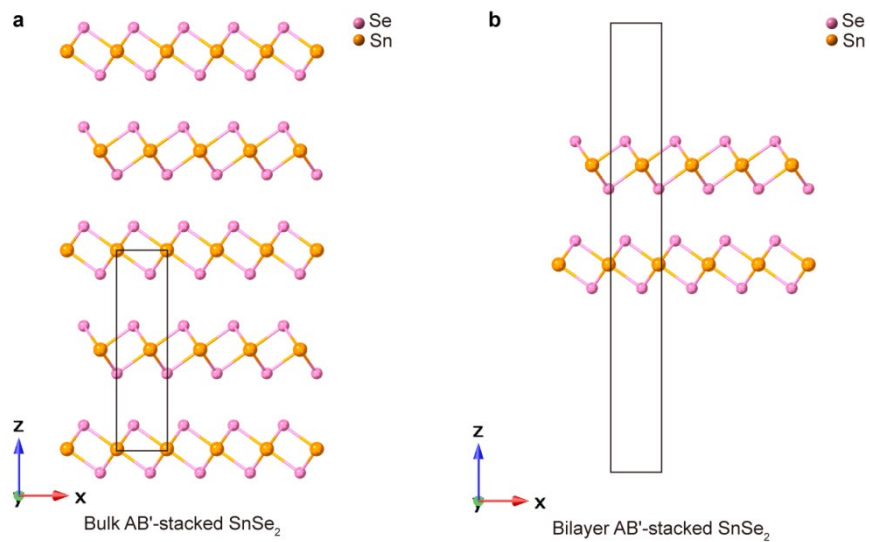
427

428 **Supplementary Note 5: SHG computational details**

429 The first-principle calculations of SHG susceptibility in this work are performed within the Quantum
 430 ESPRESSO package^{9,10}. Perdew, Becke, and Ernzerhof approximation for the exchange-correlation
 431 functional¹¹ is adopted and Van der Waals density functional corrections¹² is applied for atomic structure
 432 relaxations, where total energy changes less than 1×10^{-5} (a.u.) and all forces changes less than 1×10^{-4}
 433 (a.u.) between two consecutive iterations. Optimized norm-conserving Vanderbilt pseudopotentials^{13,14} is
 434 used with an energy cutoff of 60 Ry. We choose $24 \times 24 \times 8$ for Brillouin zone sampling in the self-consistent
 435 calculation of bulk AB'-stacked SnSe₂ (Supplementary Fig. 21a) and equivalent k-mesh for other structures.
 436 For the nonlinear optical property calculations, we follow the independent particle approximation (IPA)
 437 formalism from Ref. ¹⁵. The SHG susceptibility in the IPA is expressed as

438
$$\chi_{\alpha\beta\gamma}^{(2)}(-2\omega; \omega, \omega) = \frac{-ie^3}{\tilde{\omega}^3 \hbar^2 m^3 V} \sum_{nmk} \frac{p_{nmk}^\alpha \{p_{mlk}^\beta, p_{lnk}^\gamma\}}{\omega_{mnk} - 2\tilde{\omega}} \left[\frac{f_{nlk}}{\omega_{lnk} - \tilde{\omega}} + \frac{f_{mlk}}{\omega_{mlk} - \tilde{\omega}} \right]$$

439 where $\hbar\omega_{nmk} = E_{nk} - E_{mk}$, $f_{nlk} = f_{nk} - f_{lk}$, $p_{nmk}^\alpha = \langle \psi_{nk} | p^\alpha | \psi_{mk} \rangle$, $\tilde{\omega} = \omega + i\eta$. f_{nk} is the occupation function. E_{nk}
 440 and ψ_{nk} are the single-particle energies and wave functions obtained from DFT calculation. $i\eta$ is a small
 441 imaginary part which originates from the adiabatic switching-on process in the perturbation theory for
 442 the derivation of $\chi_{\alpha\beta\gamma}^{(2)}$. In the practical calculations, we choose $\eta = 0.05$ eV to represent the damping
 443 effect from the environment¹⁶. We use $36 \times 36 \times 12$ k-mesh and include 26 valence and 26 conduction
 444 bands for the calculation of $\chi_{\alpha\beta\gamma}^{(2)}$ in bulk AB'-stacked SnSe₂ and parameters for other structures are
 445 chosen accordingly. For bilayer structure (Supplementary Fig. 21b), the cell volume V is overestimated
 446 due to the large artificial vacuum, so we renormalize $\chi_{\alpha\beta\gamma}^{(2)}$ using the bilayer thickness.



447

448 **Supplementary Fig. 37. The atomic model chosen for SHG calculations.** (a) Bulk AB'-stacked SnSe₂

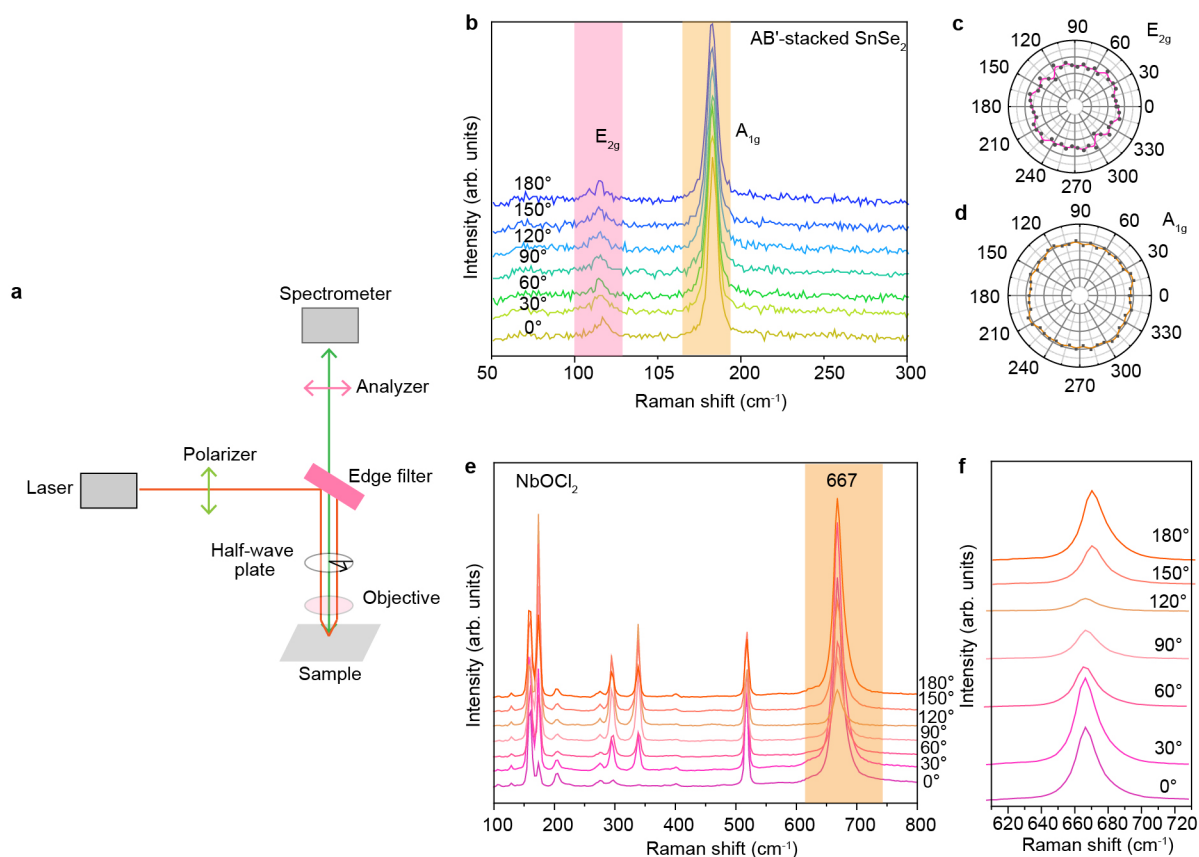
449 structure. The black rectangle corresponds to the unit cell of AB'-stacked SnSe₂ crystals. (b) The model of

450 bilayer SnSe₂ with the large artificial vacuum.

451

452 **Supplementary Note 6: Polarization dependence of Raman spectra of the AB'-stacked SnSe₂**

453 As shown in Supplementary Fig. 37b and c, the intensities of E_{2g} and A_{1g} mode are basically as circles no
 454 matter what directions were placed. To further validate the reliability of the experimental results, we
 455 performed a polarized Raman spectrum on NbOCl₂ crystal as a reference. Notably, the intensity of the 667
 456 cm⁻¹ peak exhibits a clear angular dependence, decreasing from a maximum at 0° to zero at 90°, and then
 457 gradually increasing from 90° to 180°.



458
 459 **Supplementary Fig. 38. Polarization dependence of Raman spectra of the AB'-stacked SnSe₂ with the**
 460 **532 nm excitation in parallel polarization configuration.** (a) Schematic illustrations of polarized Raman
 461 measurements. (b) Angle-dependent polarized Raman intensity of AB'-stacked SnSe₂ crystal. Polar plot of
 462 Raman intensity for typical E_{2g} mode (c) and A_{1g} mode (d). (e) Raman spectra at various polarization angles
 463 under parallel configuration. (f) Polarization-dependent Raman intensity of 667 cm⁻¹ in a NbOCl₂ crystal.

464 **Supplementary References:**

- 465 1 Blöchl, P. E. Projector augmented-wave method. *Physical Review B* **50**, 17953-17979 (1994).
- 466 2 Kresse, G. & Joubert, D. From ultrasoft pseudopotentials to the projector augmented-wave
467 method. *Physical Review B* **59**, 1758-1775 (1999).
- 468 3 Kresse, G. & Furthmüller, J. Efficient iterative schemes for ab initio total-energy calculations using
469 a plane-wave basis set. *Physical Review B* **54**, 11169-11186 (1996).
- 470 4 Bhaviripudi, S., Jia, X., Dresselhaus, M. S. & Kong, J. Role of kinetic factors in chemical vapor
471 deposition synthesis of uniform large area graphene using copper catalyst. *Nano Lett.* **10**, 4128-
472 4133 (2010).
- 473 5 Xu, M. *et al.* Reconfiguring nucleation for CVD growth of twisted bilayer MoS₂ with a wide range
474 of twist angles. *Nat. Commun.* **15**, 562 (2024).
- 475 6 Zhang, Z. *et al.* Robust epitaxial growth of two-dimensional heterostructures,
476 multiheterostructures, and superlattices. *Science* **357**, 788-792 (2017).
- 477 7 Tang, L., Tan, J., Nong, H., Liu, B. & Cheng, H.-M. Chemical vapor deposition growth of two-
478 dimensional compound materials: Controllability, material quality, and growth mechanism. *Acc.*
479 *Mater. Res.* **2**, 36-47 (2021).
- 480 8 Lee, J. H. *et al.* Dynamic layer rearrangement during growth of layered oxide films by molecular
481 beam epitaxy. *Nat. Mater.* **13**, 879-883 (2014).
- 482 9 Giannozzi, P. *et al.* QUANTUM ESPRESSO: a modular and open-source software project for
483 quantum simulations of materials. *J. Phys.: Condens. Matter* **21**, 395502 (2009).
- 484 10 Giannozzi, P. *et al.* Advanced capabilities for materials modelling with Quantum ESPRESSO. *J. Phys.:*
485 *Condens. Matter* **29**, 465901 (2017).
- 486 11 Perdew, J. P., Burke, K. & Ernzerhof, M. Generalized Gradient Approximation Made Simple. *Phys.*
487 *Rev. Lett.* **77**, 3865-3868 (1996).
- 488 12 Klimeš, J., Bowler, D. R. & Michaelides, A. Van der Waals density functionals applied to solids.
489 *Physical Review B* **83**, 195131 (2011).
- 490 13 Hamann, D. R. Optimized norm-conserving Vanderbilt pseudopotentials. *Physical Review B* **88**,
491 085117 (2013).
- 492 14 Schlipf, M. & Gygi, F. Optimization algorithm for the generation of ONCV pseudopotentials.
493 *Comput. Phys. Commun.* **196**, 36-44 (2015).

- 494 15 Leitsmann, R., Schmidt, W. G., Hahn, P. H. & Bechstedt, F. Second-harmonic polarizability
495 including electron-hole attraction from band-structure theory. *Physical Review B* **71**, 195209
496 (2005).
- 497 16 Giuliani, G. & Vignale, G. *Quantum Theory of the Electron Liquid*. (Cambridge University Press,
498 2005).
- 499